



## R2RAM 640073 H2020 Project

Cristiano Calligaro

RedCat Devices - [c.calligaro@redcatdevices.it](mailto:c.calligaro@redcatdevices.it)



# Outline

- ❑ R2RAM Consortium
- ❑ R2RAM Goals
- ❑ R2RAM Technology
- ❑ R2RAM Test Vehicle
- ❑ R2RAM Testing approach



# R2RAM Consortium

The IHP is an institute of the Leibniz Association and conducts research and development of silicon-based systems and ultra high-frequency circuits and technologies including new materials. It develops innovative solutions for application areas such as wireless and broadband communication, aerospace, biotechnology and medicine, automotive industry, security technology and industrial automation.

**Key Person and Project Coordinator: Christian Wenger**



IUNET (Italian Universities Nano-Electronics Team), is a non-profit Organization, aimed to lead and coordinate the effort of the major Italian university teams in the field of silicon-based nanoelectronic device modelling and characterization. Current members of IUNET are the Universities of Bologna, Calabria, Ferrara, Modena e Reggio Emilia, Padova, Pisa, Udine, Roma “La Sapienza” and the Politecnico of Milano. **Key Person: Prof. Piero Olivo**



The University of Jyväskylä (JYU) is one of the largest universities in Finland. Department of Physics (JYFL) of the university belongs to the Faculty of Mathematics and Science. Accelerator laboratory of JYFL has operated very successfully as one of the Large Research Access Infrastructures in the FP4 - FP7 programmes of the EU since 1996 (ENSAR for 2013-2014) and acted as a FP5 Marie Curie Training Site. Since 2005 laboratory's RADiation Effects Facility, RADEF has been qualified to one of the External European Component Irradiation Facilities of European Space Agency, ESA. **Key Person: Prof. Ari Virtanen**



UNIVERSITY OF JYVÄSKYLÄ

RedCat Devices (RCD) is a privately held fabless semiconductor company involved in several fields of research concerning memories (volatile and non volatile), analog components (ADCs, DACs) and standard digital libraries for special applications. In the last eight years RCD has been involved in several R&D projects including FP7 262890 SkyFlash in the role of coordinator. **Key Person: Cristiano Calligaro**





# R2RAM Goals



Development and design of a radiation hard non-volatile memory technology by using standard CMOS silicon processing.

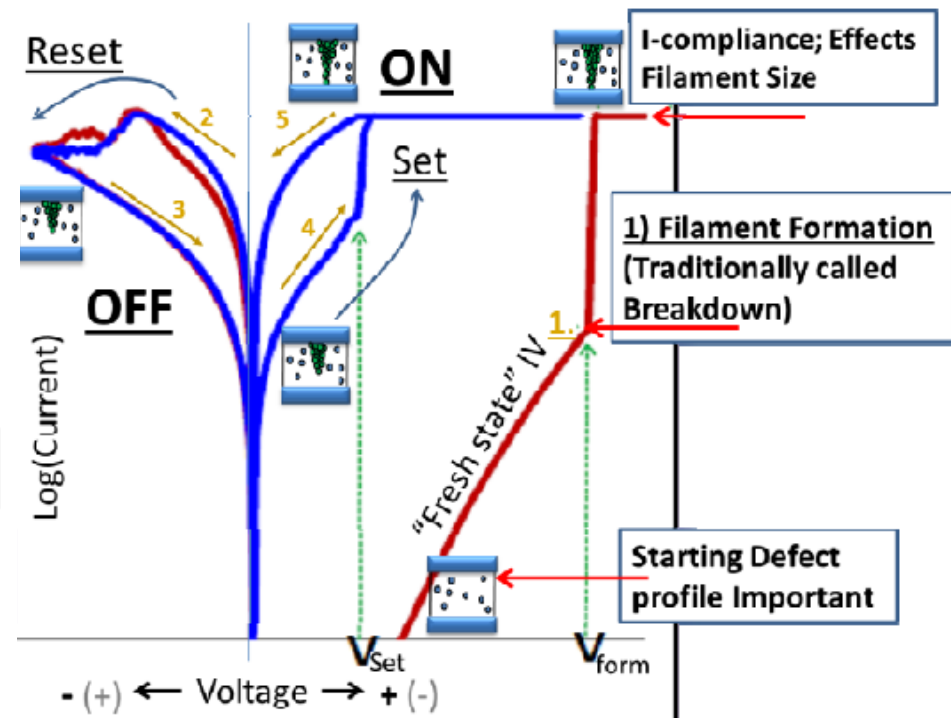
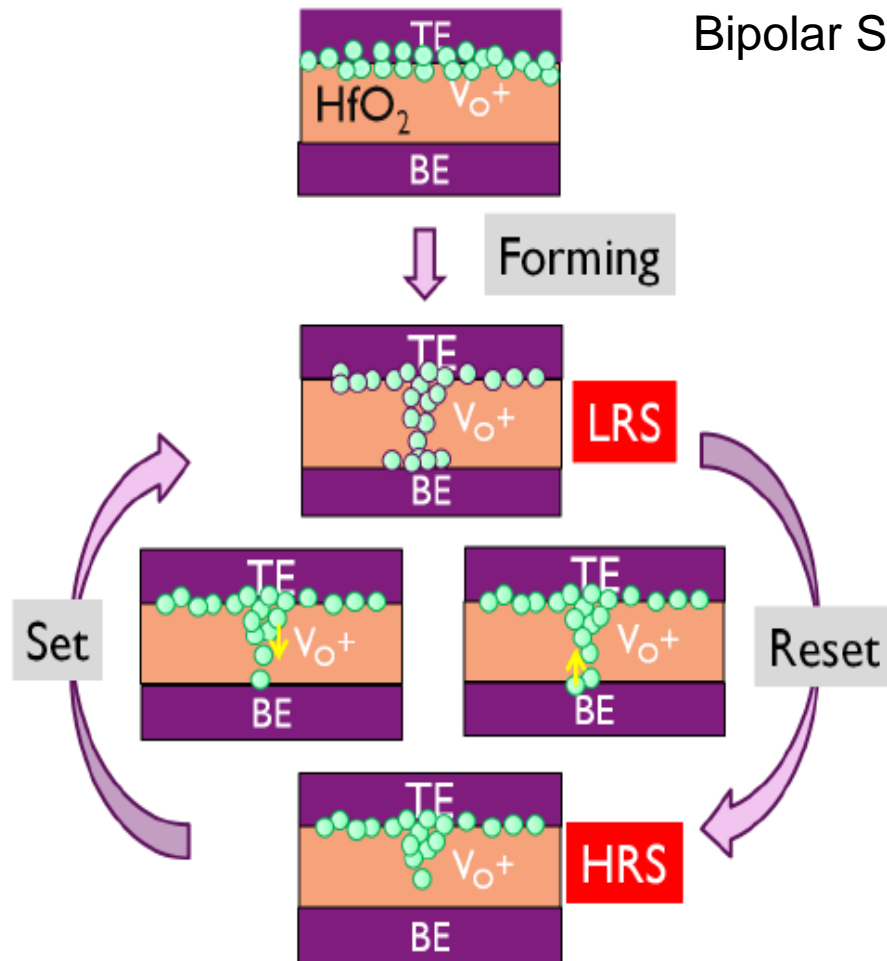
## New **R2RAM** approach:

Using the Resistive random-access memory (RRAM) technology

[www.r2ram.eu](http://www.r2ram.eu)



## Bipolar Switching effect in Ti/HfO<sub>2</sub> based MIM cells

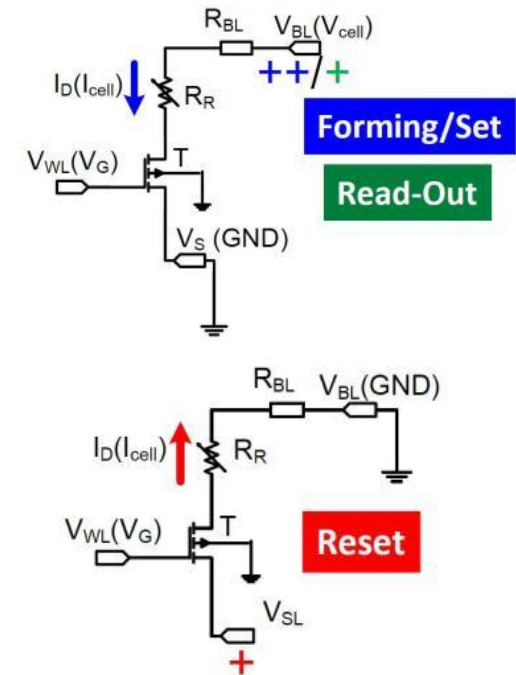
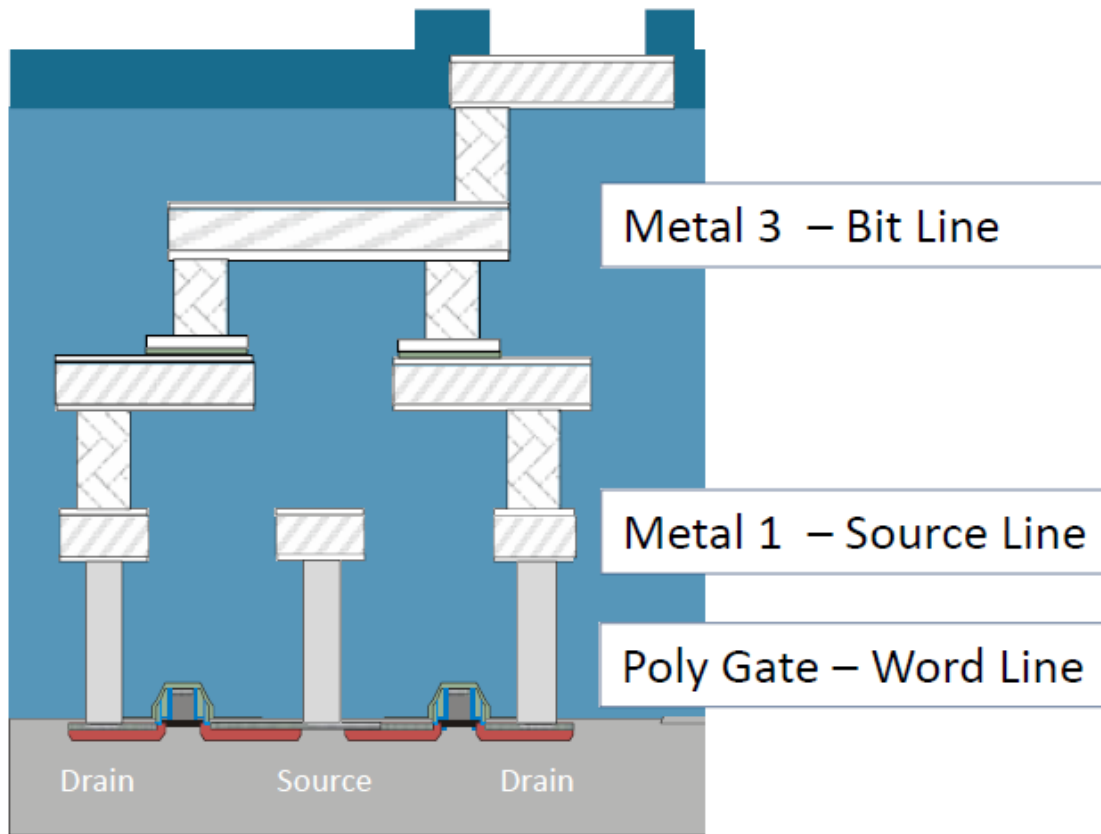




# Schematic 1T1R Device



## TiN/HfO<sub>2</sub>/Ti/TiN 1T1R Devices:

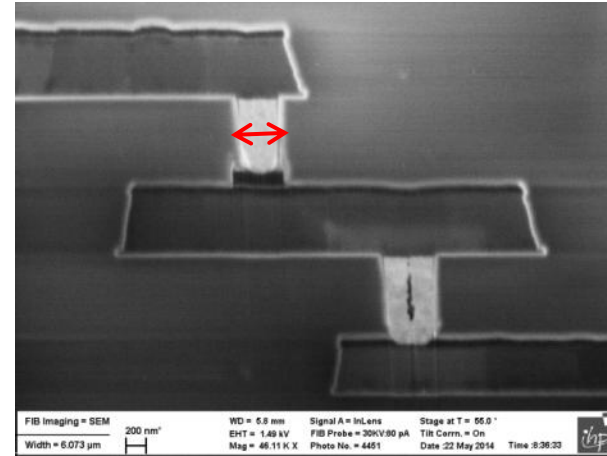




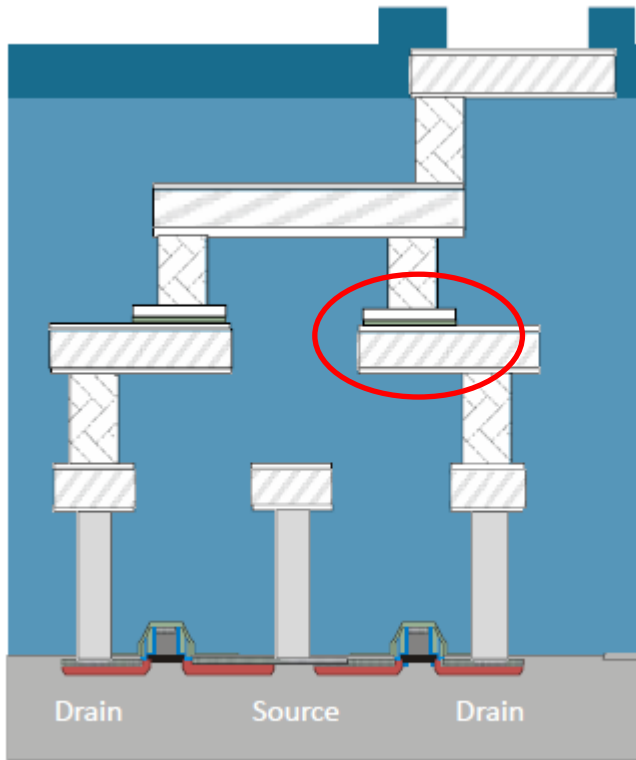
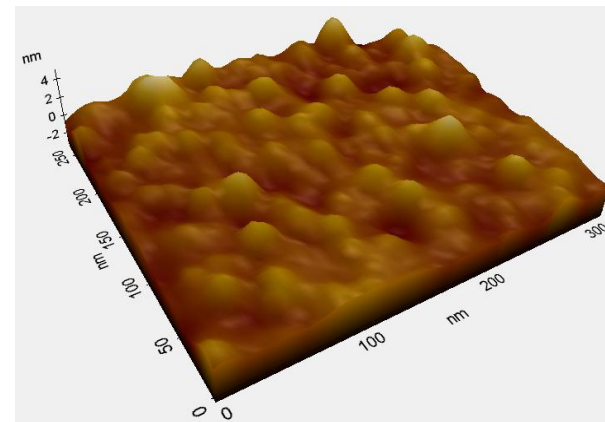
# Schematic 1T1R Device (Integration Issues)



## 1. Cell size: > 500 nm



## 2. Surface roughness of Met 2: > 2 nm



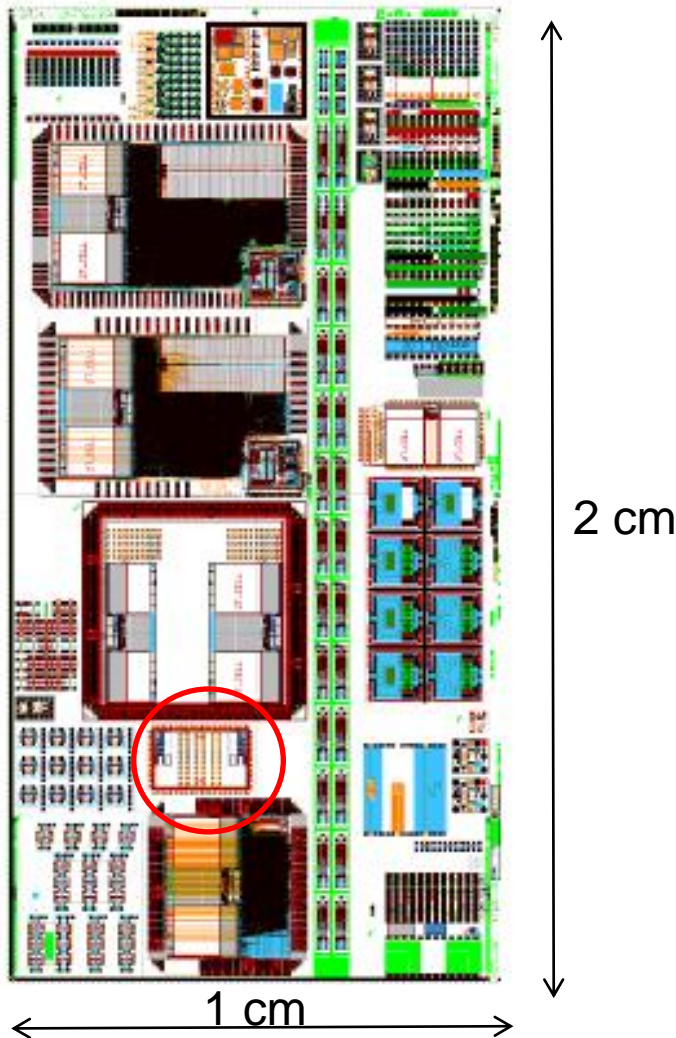
## 3. Final anneal at 400 °C for 30 min



# MPW Approach



## Testfield 284



### Cost sharing (Multi Project Wafer):

Every circuit designer is using the same design kit

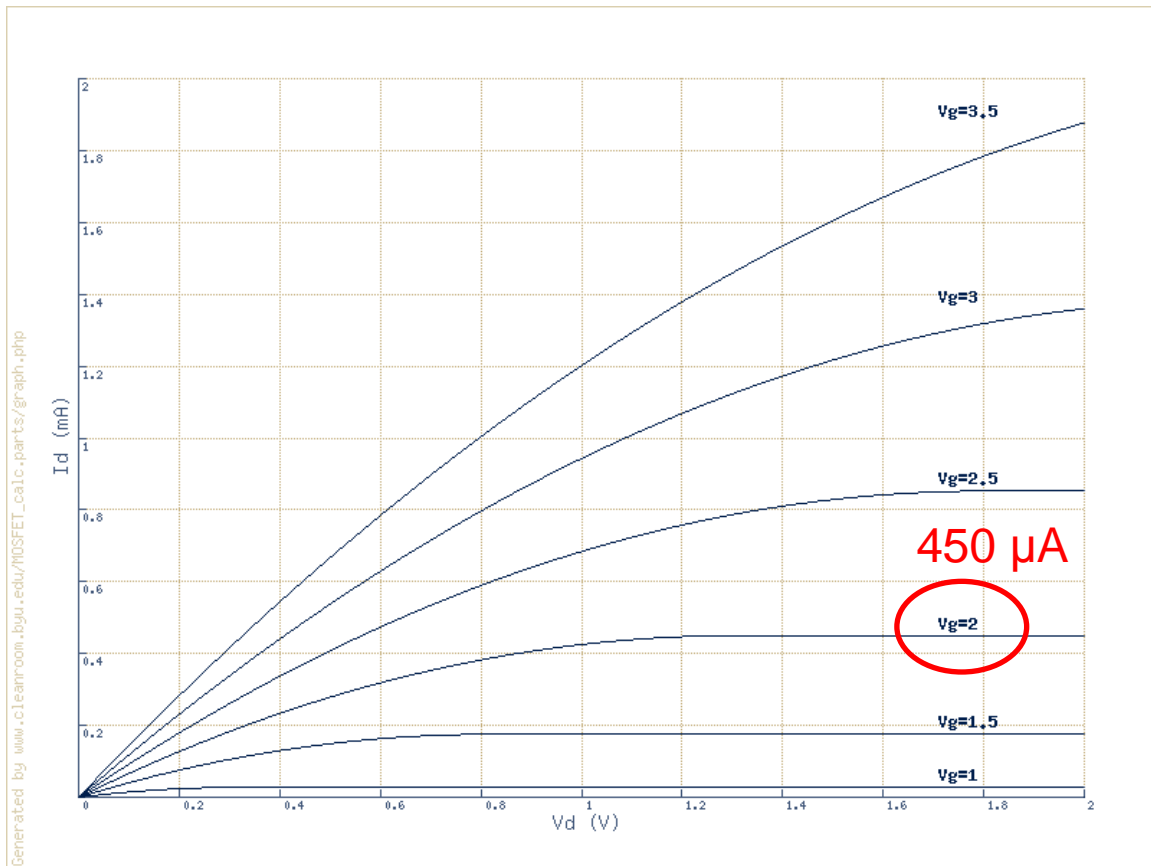
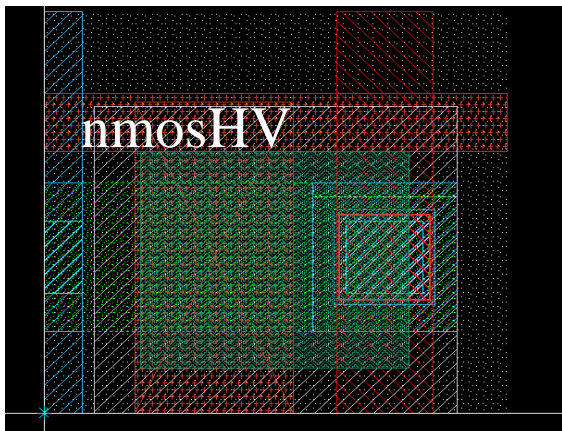
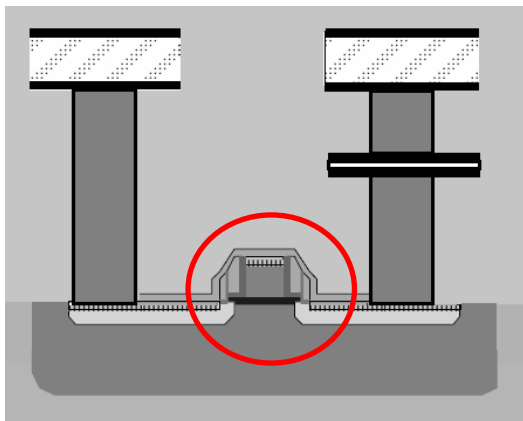
Process flow is equal until finalized Metal 2, split of RRAM wafers

### Required additional process steps:

- $\text{HfO}_2$  deposition by CVD or ALD
- Ti/TiN deposition by PVD
- TiN/Ti/ $\text{HfO}_2$  etching by RIE



# Choice of NMOS Select Transistor



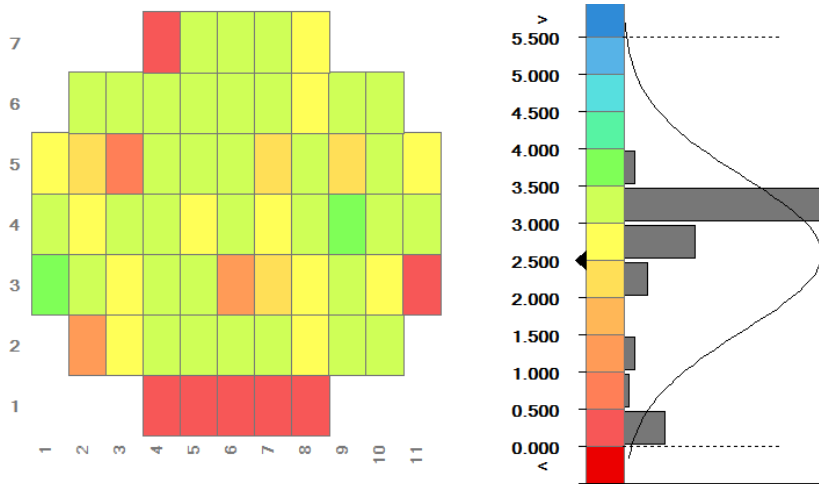
Length:  $0.3 \mu\text{m}$   
Width:  $0.3 \mu\text{m}$   
Oxide:  $5.0 \text{ nm}$



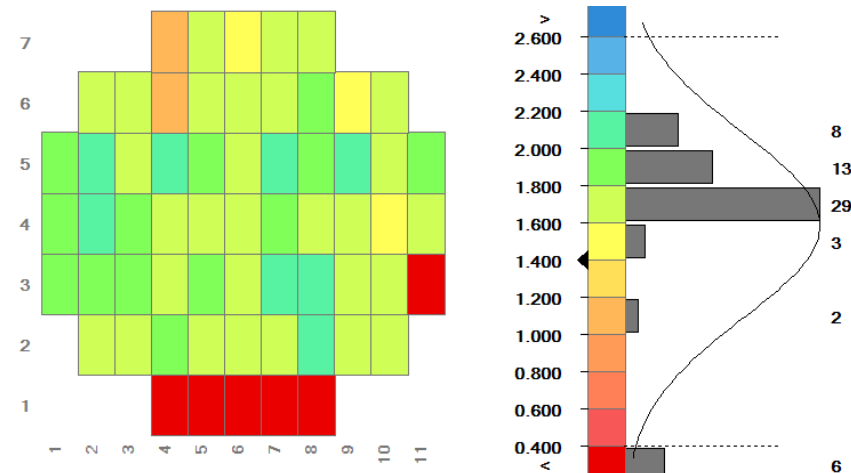
# Yield poly-crystalline HfO<sub>2</sub>



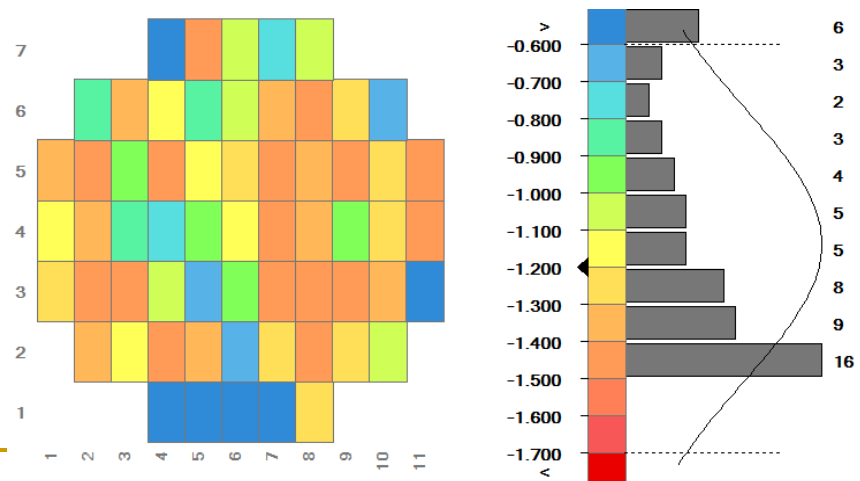
Forming



Set



Reset



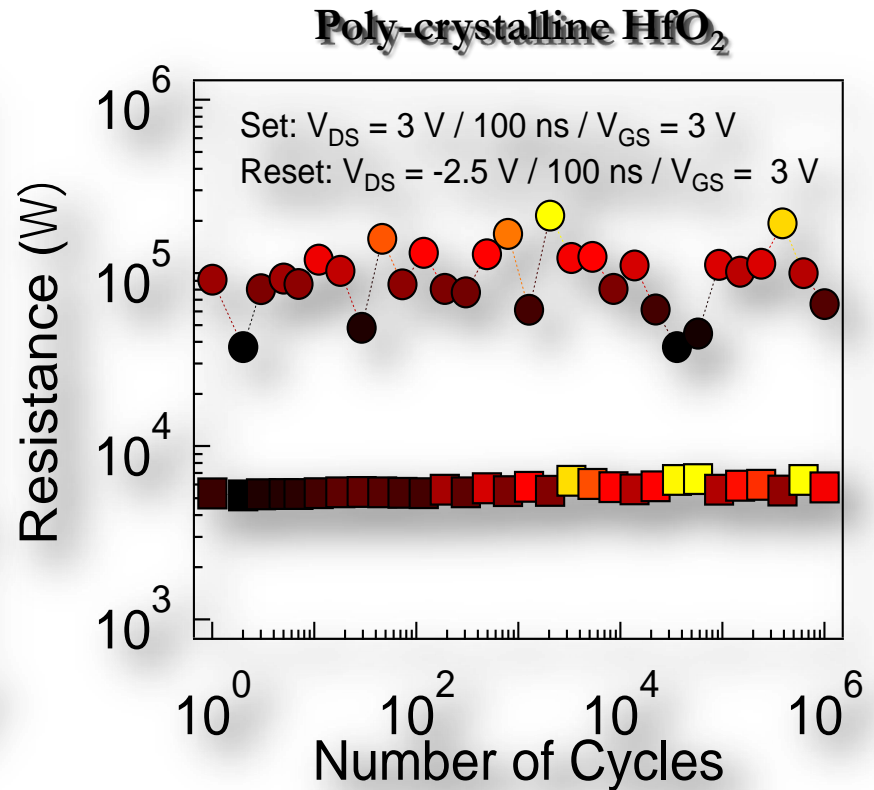
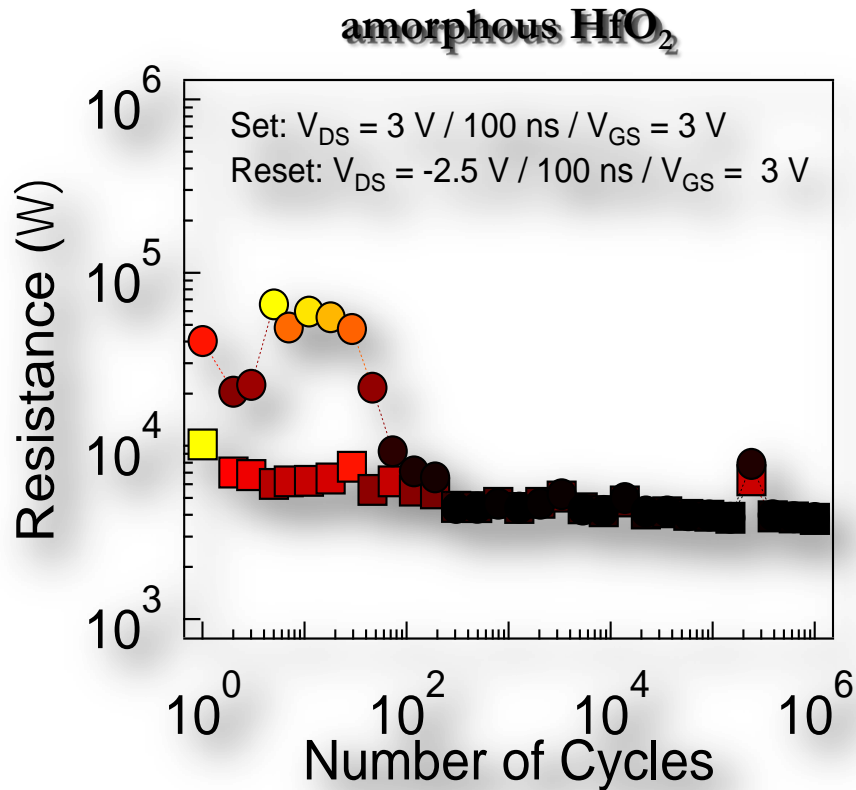
$V_{\text{read}} = 0.2 \text{ V}$ ,  $V_{\text{set,WL}} = 2 \text{ V}$ ,  $V_{\text{set,BL}} = 2 \text{ V}$ ,  
 $V_{\text{reset,WL}} = 3 \text{ V}$ ,  $V_{\text{reset,SL}} = 1.5 \text{ V}$



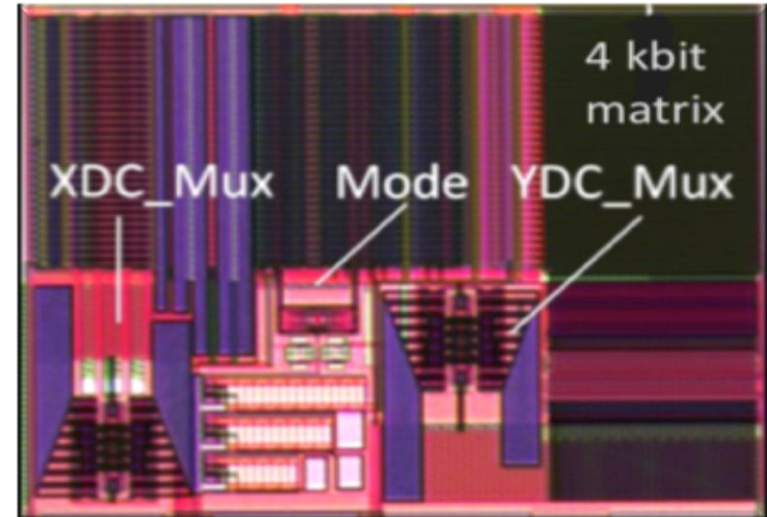
# Endurance of single 1T1R device



Stable endurance for poly  $\text{HfO}_2$

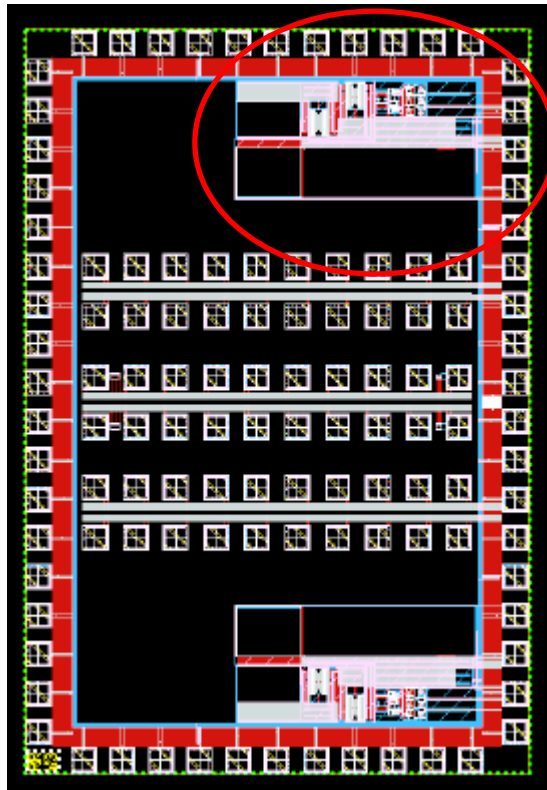








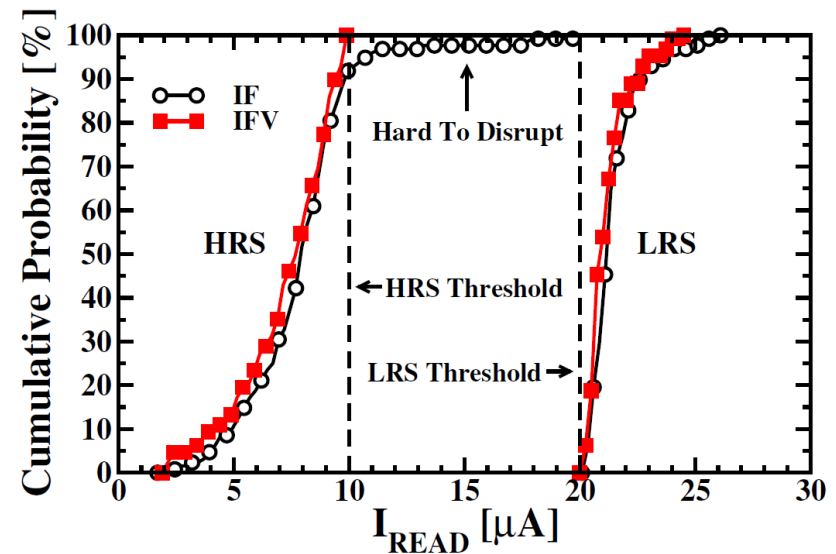
# 4Kbit Test Vehicle (Test at Univ. Ferrara)



4kbit array

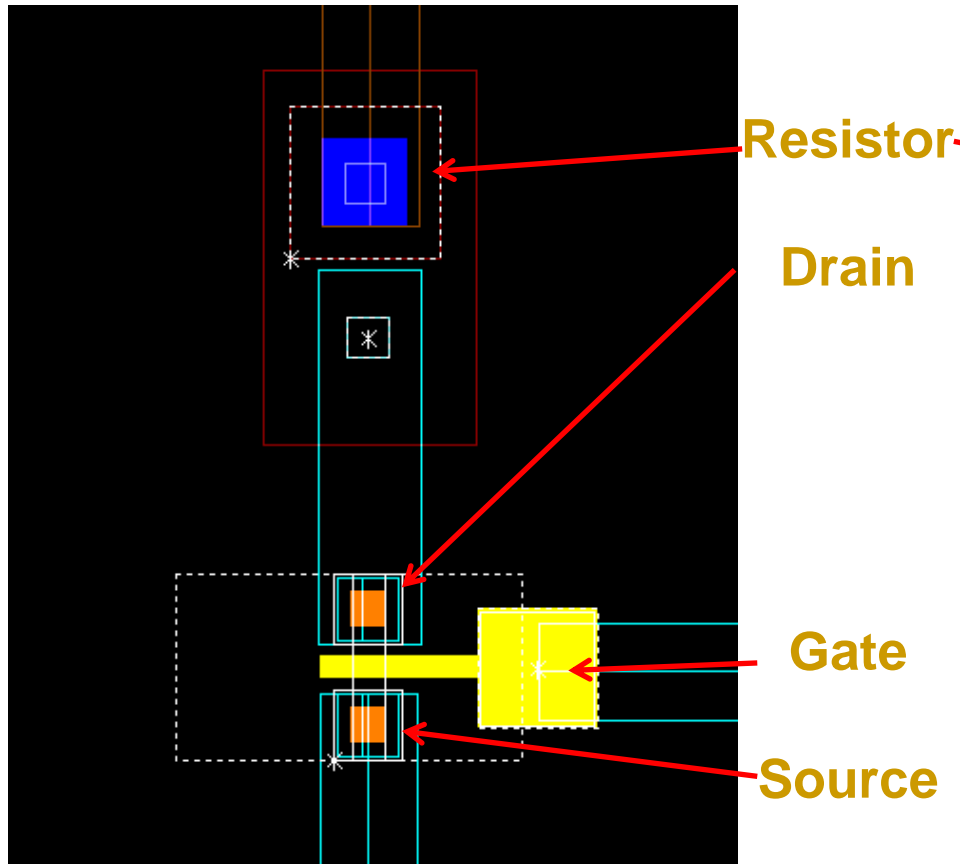


Incremental Form and Verify (IFV):

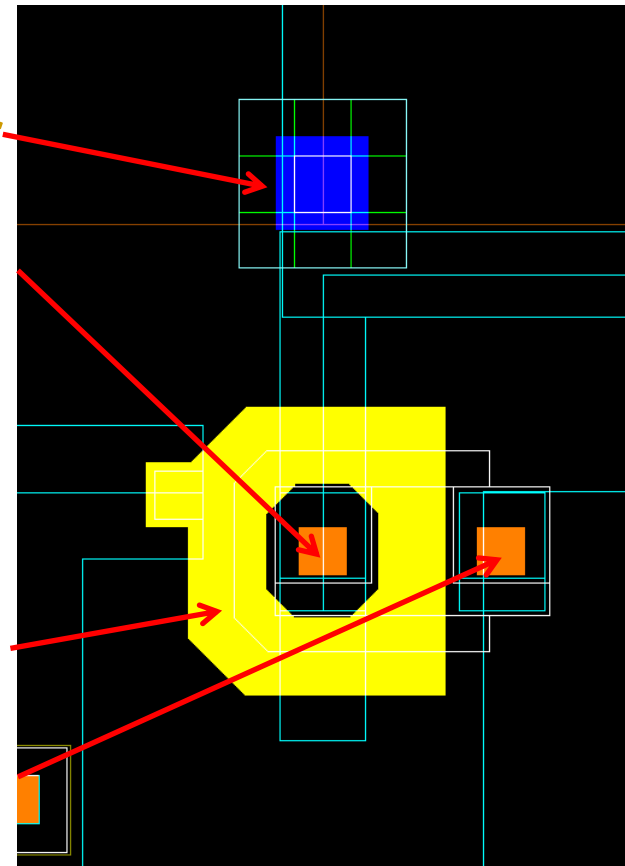




## Standard cell:



## Rad-hard cell:





# R2RAM Test Vehicle (The SkyFlash heritage)

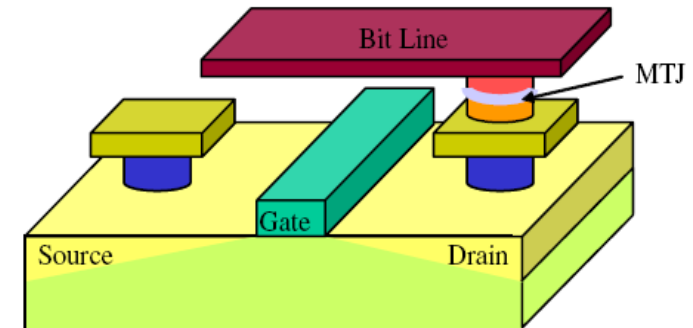
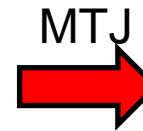


- SkyFlash has been focused on Nitride Flash cells but many blocks are in common with others NVM technologies.



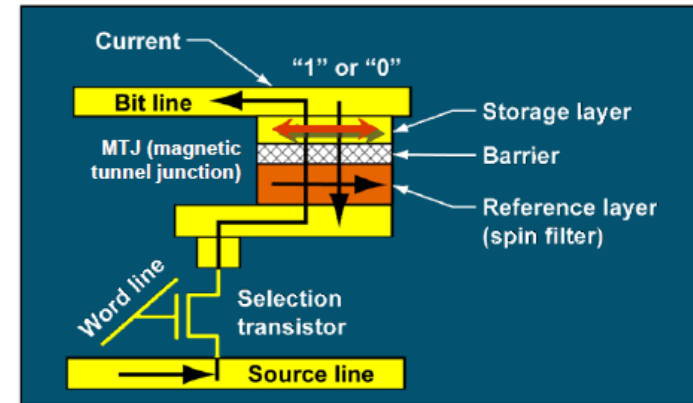
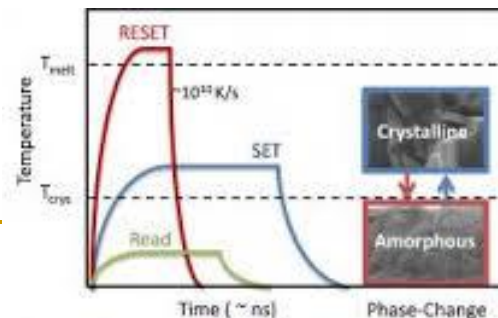
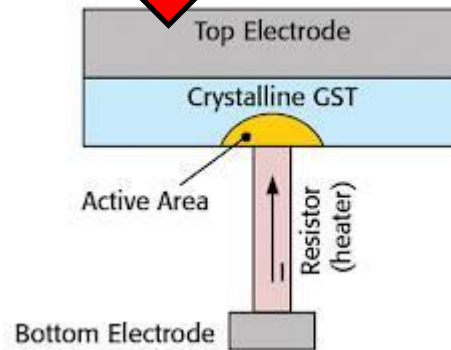
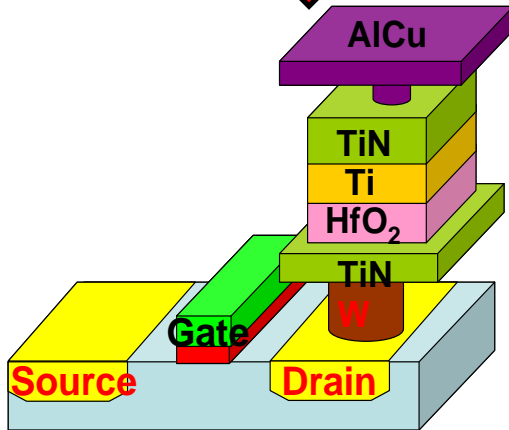
## SkyFlash Roadmap

decoders, sense amplifiers, memory architecture, double cell, charge pumps, bandgap references, I/O pads, HV distribution, level shifters, S-Flash, CEONOS, final stages, ATDs, etc...



RRAM

PCM



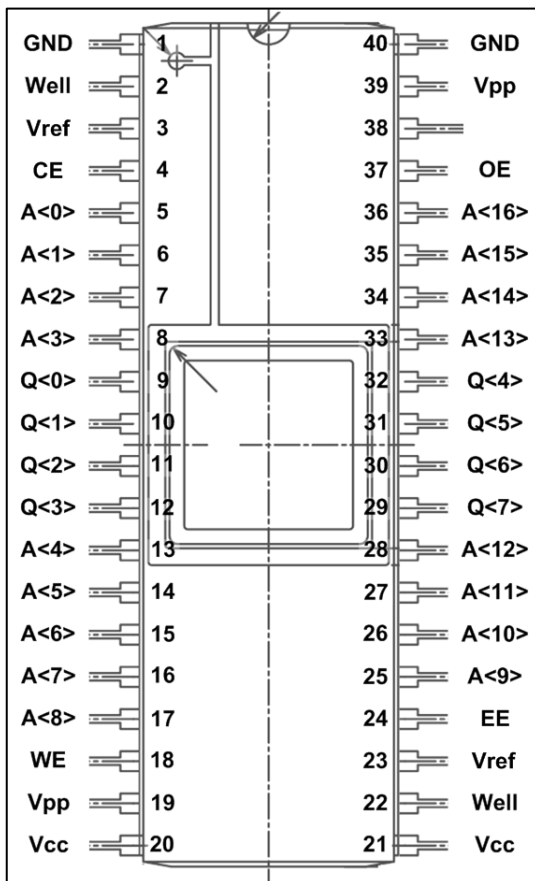
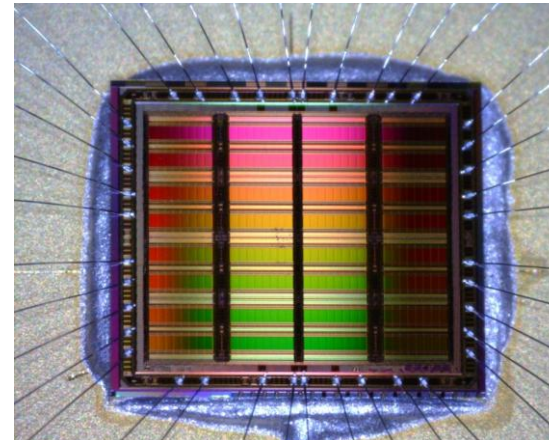
RedCat Devices



# SkyFlash Test Vehicles



## 1Mbit (128kbit x8)



### Prototype Code

### Description

RC27F1024SKY1

1Mbit OTP with external HV

RC27F1024SKY2

1Mbit OTP with internal charge pump

RC27F1024SKY3

1Mbit OTP with internal charge pump and reference array

RC27F1024SKY4

1Mbit OTP with internal charge pump and bgref

RC27F1024SKY5

1Mbit OTP with charge pump for erasing

RC27F1024SKY6

1Mbit OTP refinement of SKY5

RC28F1024SKY1

1Mbit NVM based on SKY4 (CEONOS replacement)

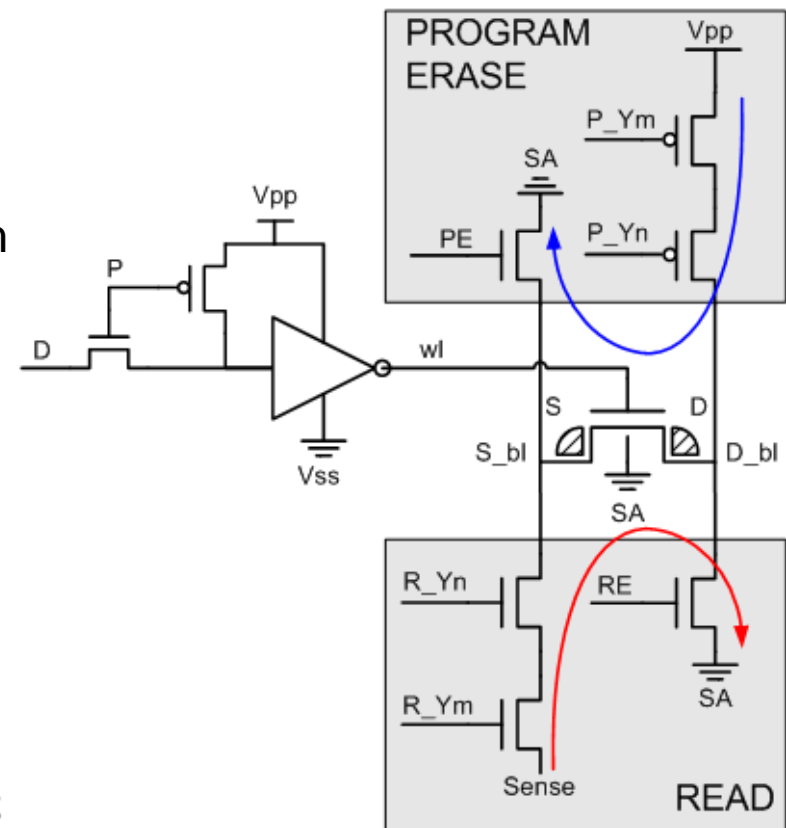
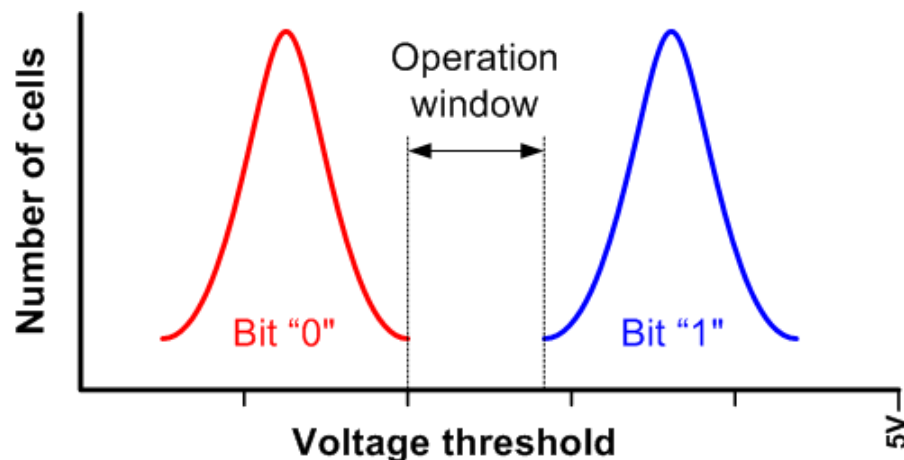


# From NROM to ReRAM 1/2



Cell program and erase is based on hot carrier mechanism (CHE) and hot holes generated by band-to-band (BTB) tunneling. The injection of charge in the nitride produces a shift on the threshold voltage. The programming is done from the drain side with voltages of 5-6V using 3.3V transistors.

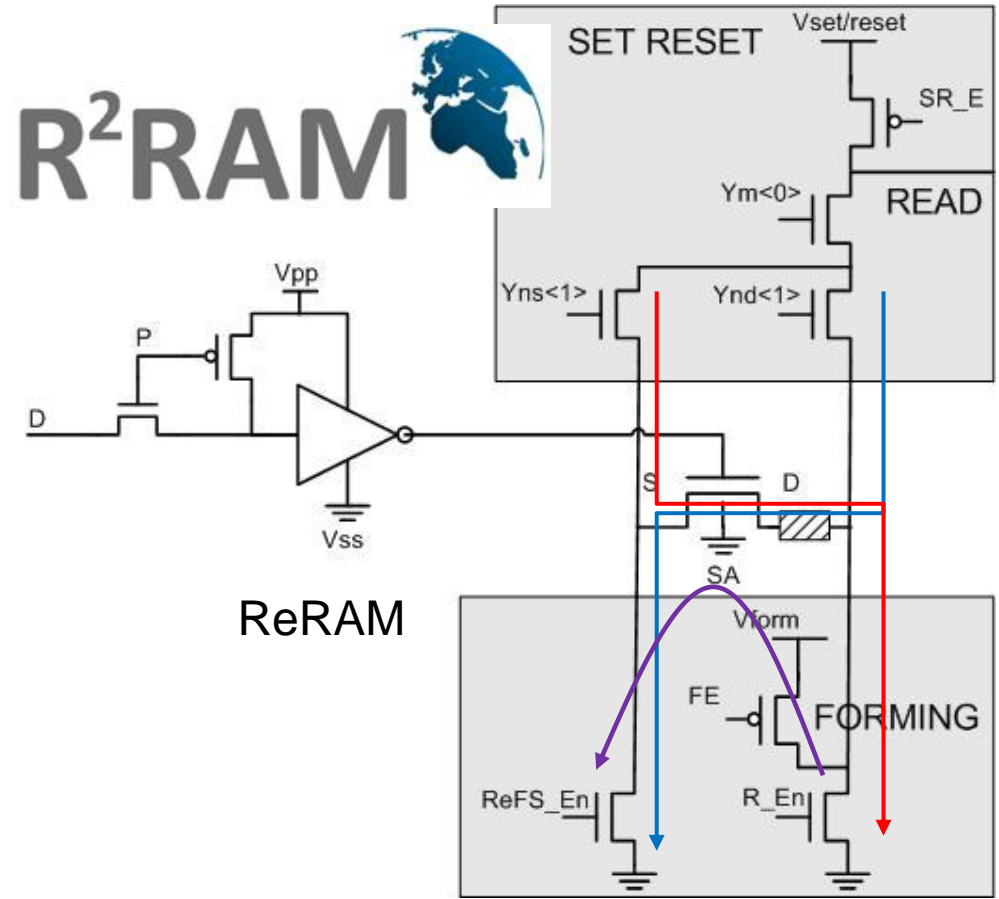
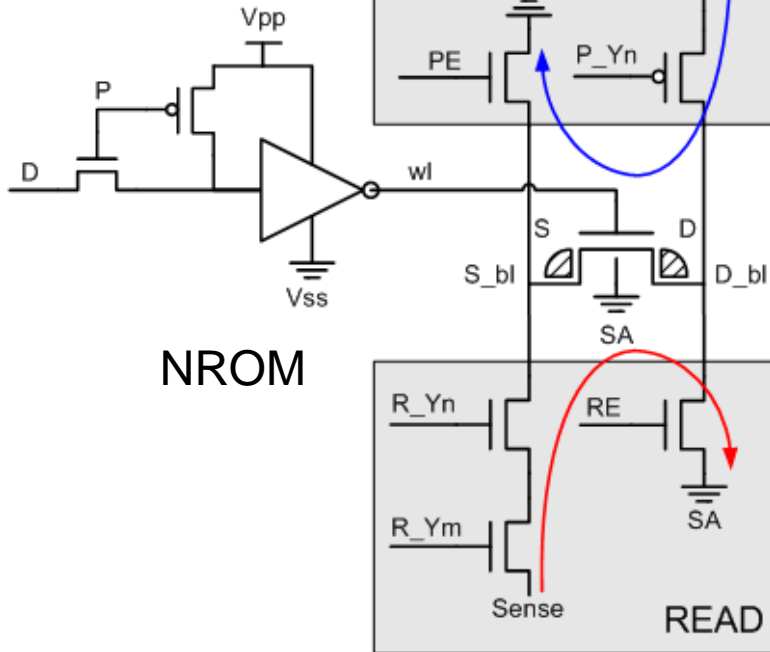
Each bit is represented with different  $V_{th}$  and the distance between them is the operation window. Reading is done on the reverse direction of programming (source), allowing to separate high voltage circuitry from the reading stage.





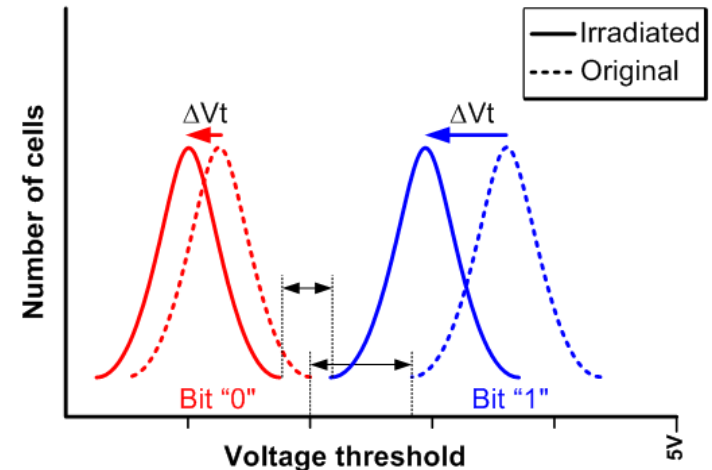
# From NROM to ReRAM 2/2

Despite the differences between the two cells, the main goal is to maintain the same architectural approach in the test vehicle





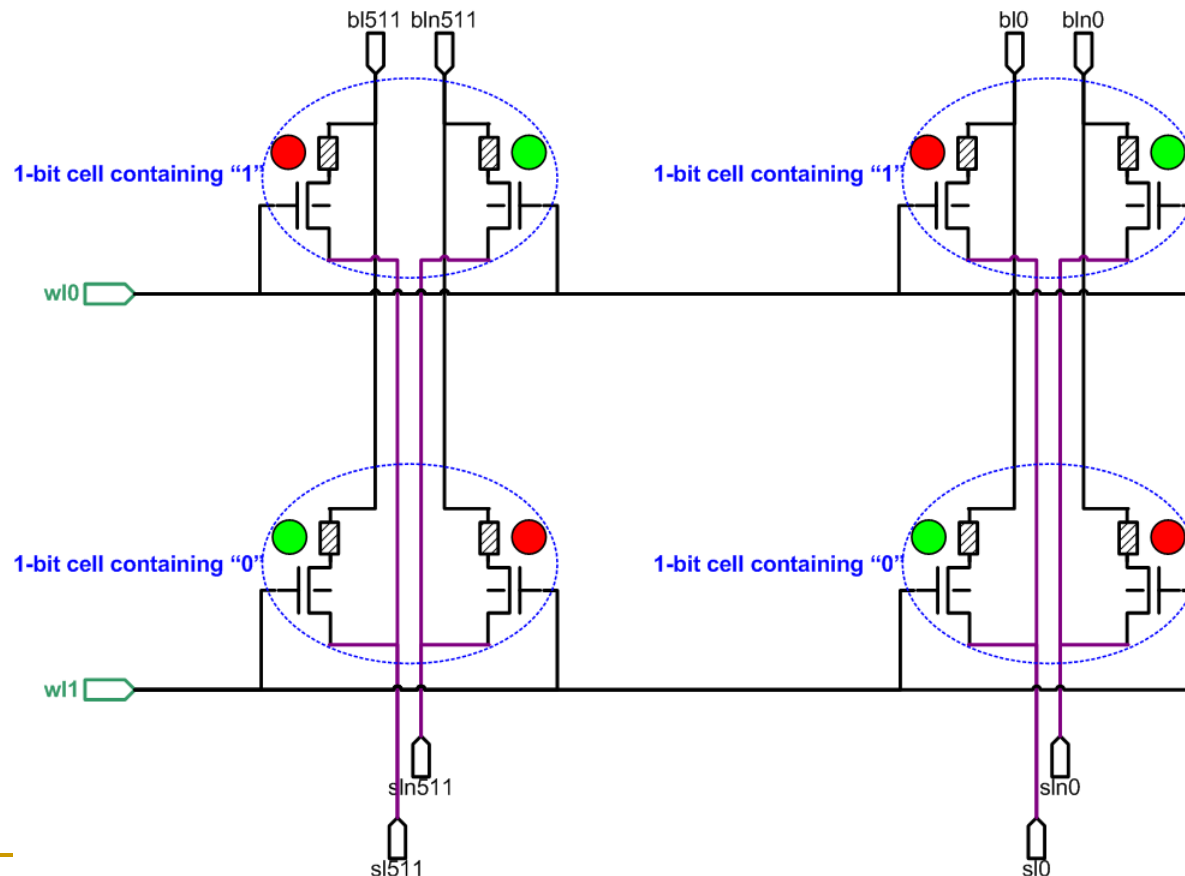
# R<sup>2</sup>RAM





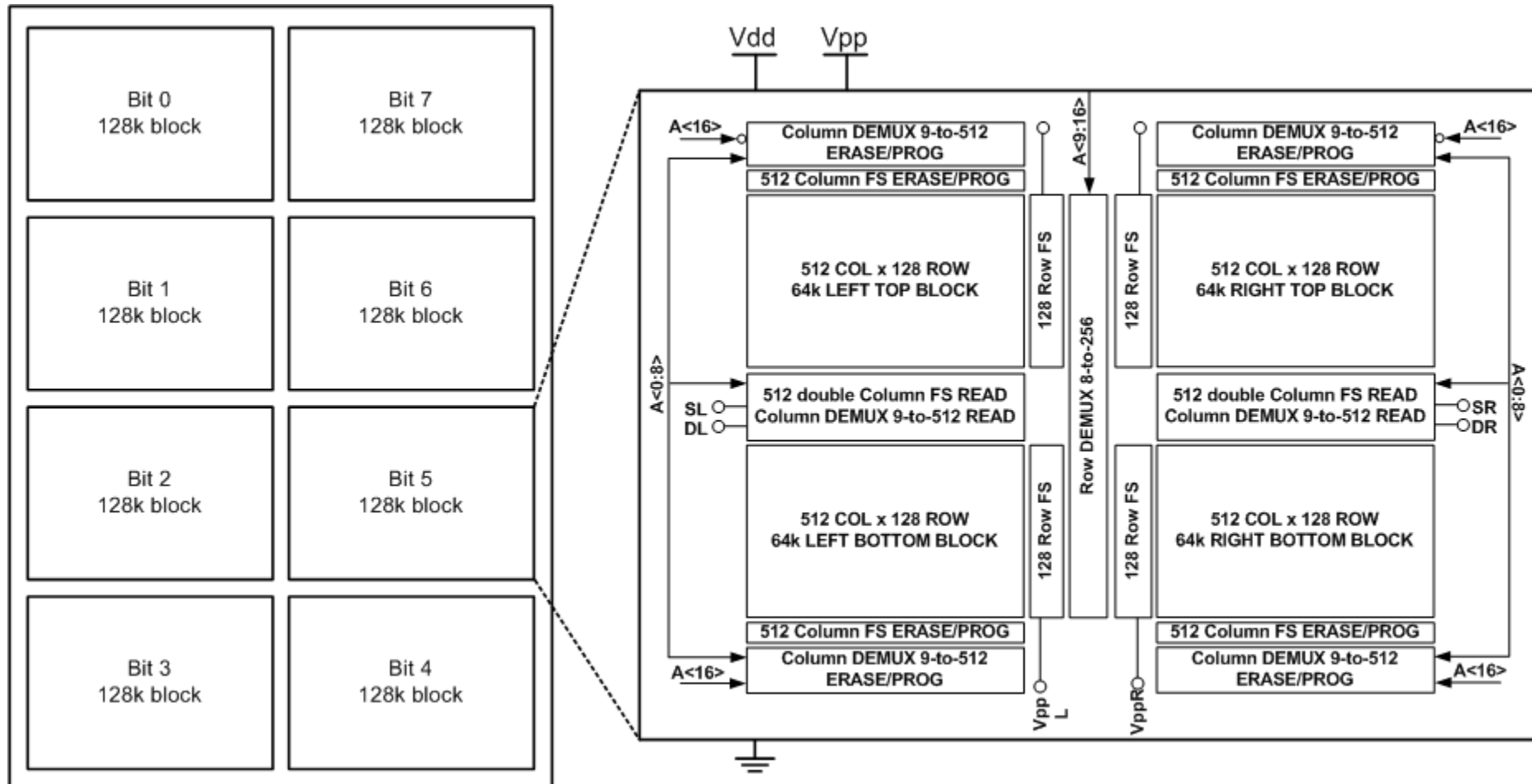
# Differential Cell in R2RAM

The differential approach in memory array foresees a low resistance cell on the left and a high resistance cell on the right. We call this status “1”. Vice-versa for “0”. This architectural approach does not require ANY reference cell.





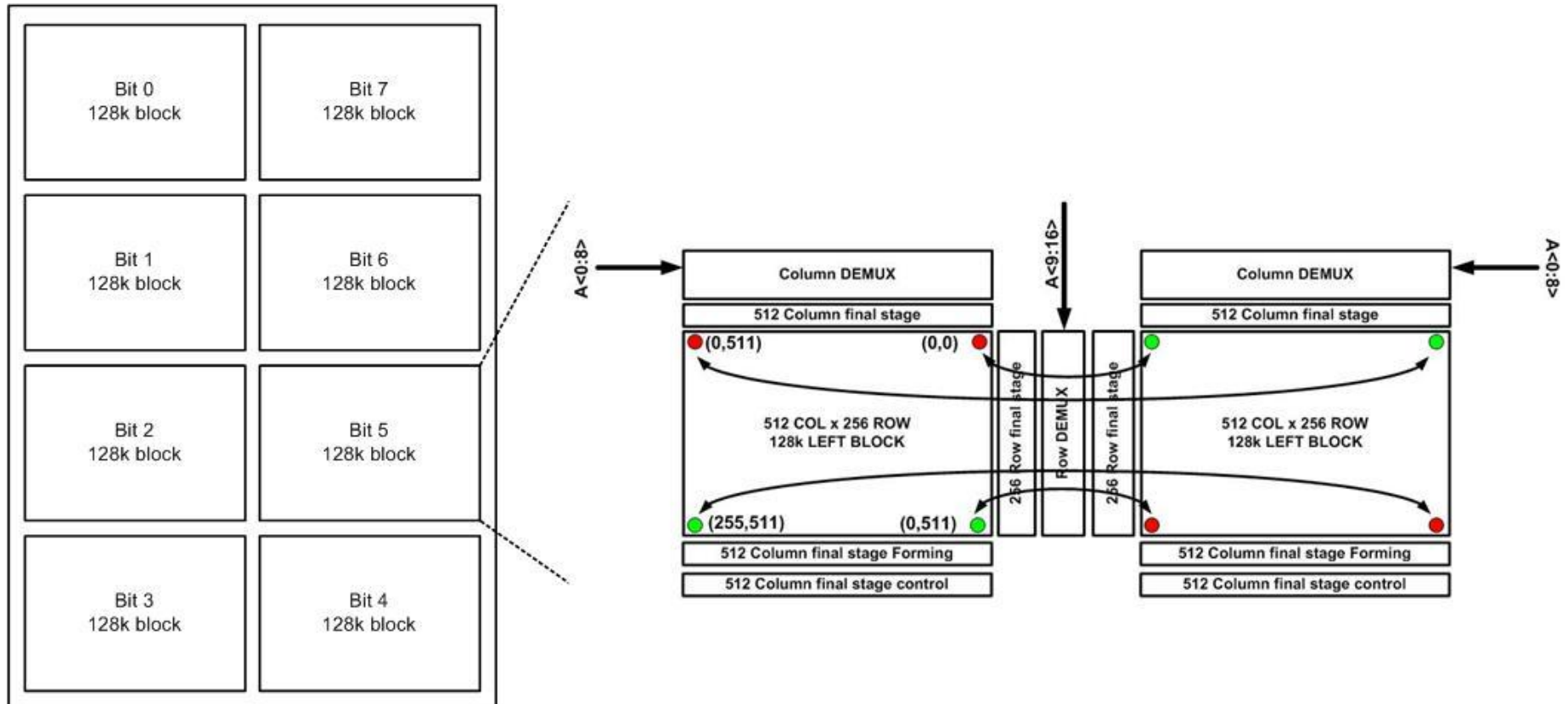
# SkyFlash 1Mbit (RC27F1024SKYn)





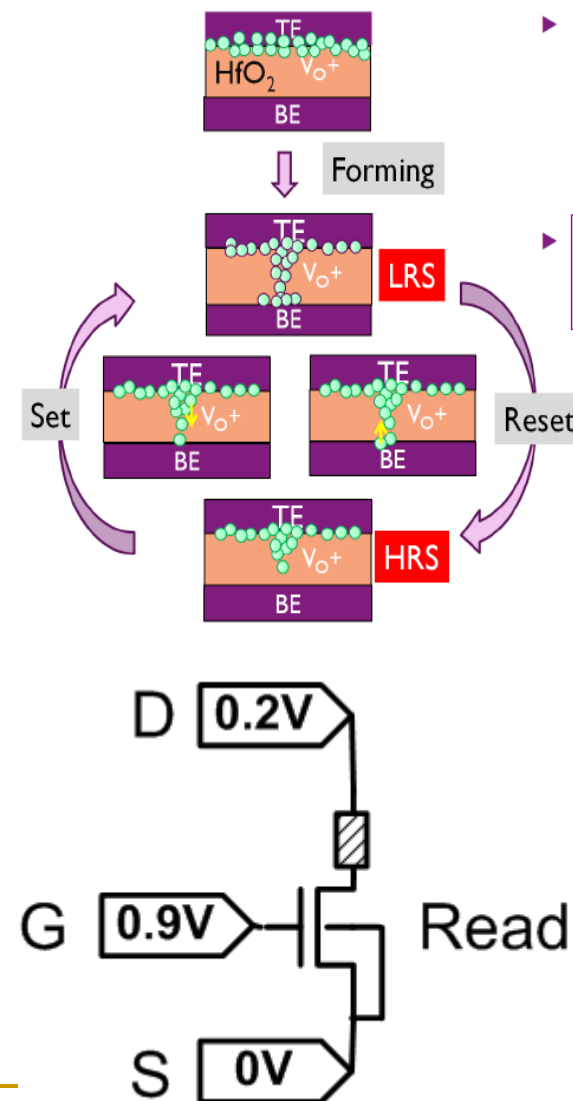
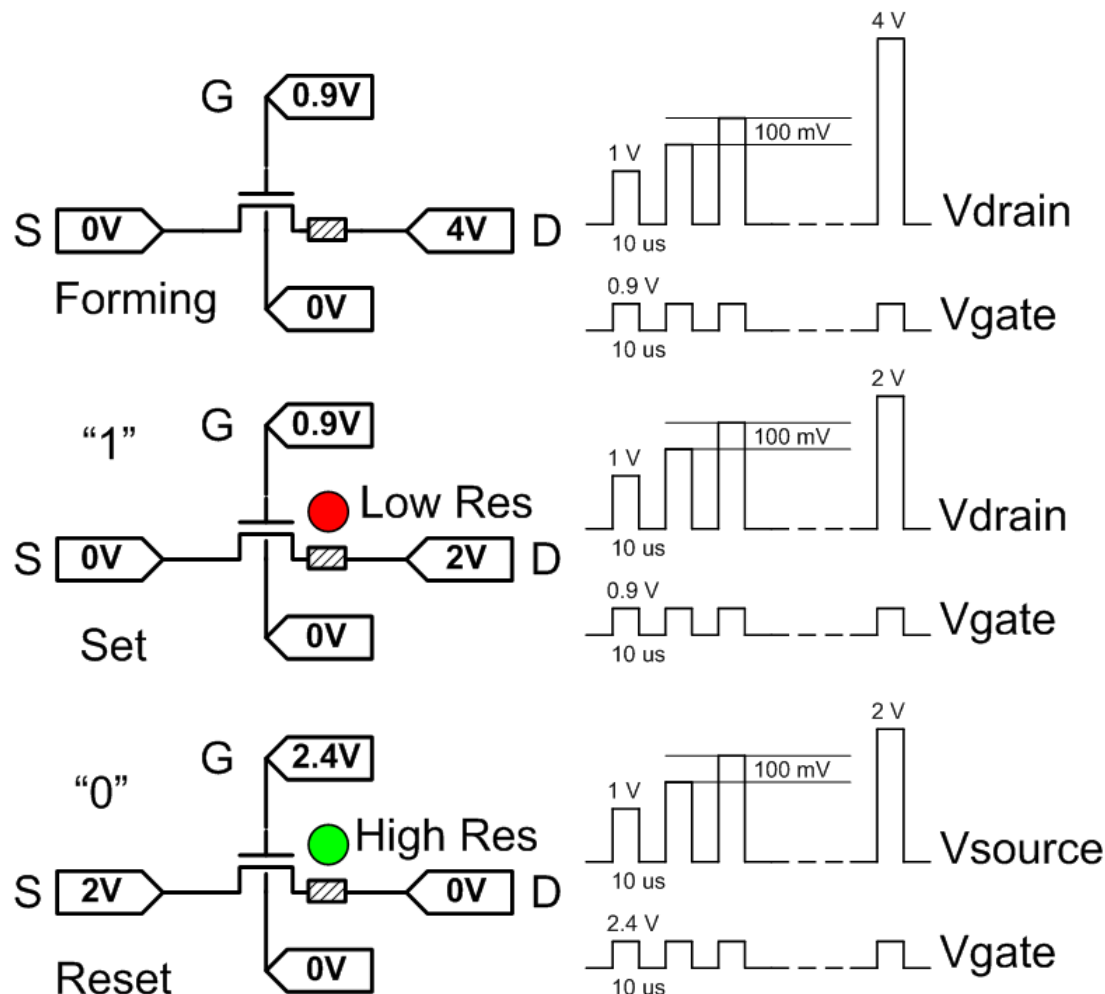
# R2RAM 1Mbit (RC28F1024R2RAMn)

The independence of each bit (independent final stages, ATDs, etc...) guarantees resistance to MBUs.



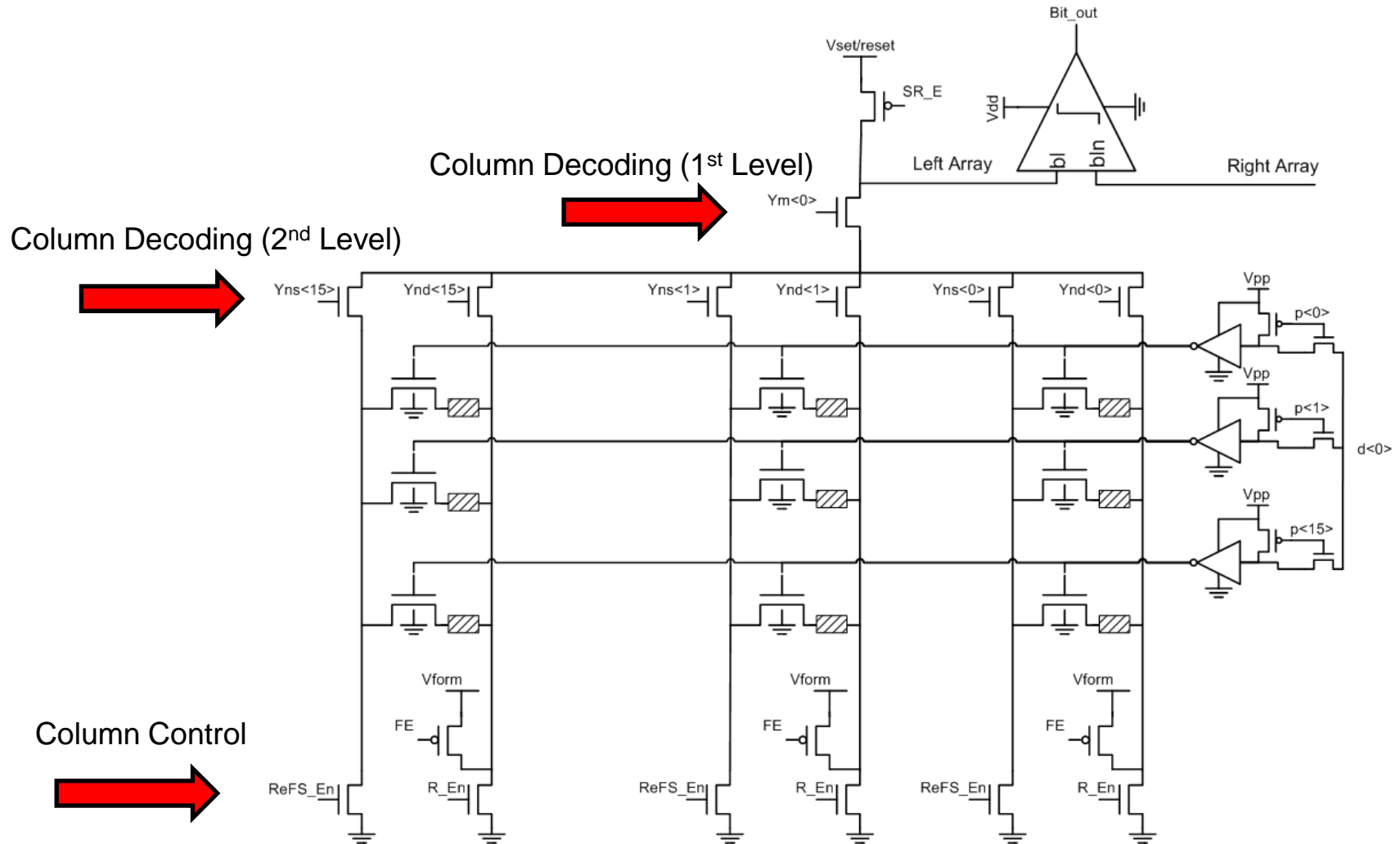


# ReRAM Cell Working Conditions





# Architectural Approach (16 x 16 Bank)






$$V_{\text{forming}} = 4 \text{ V}$$

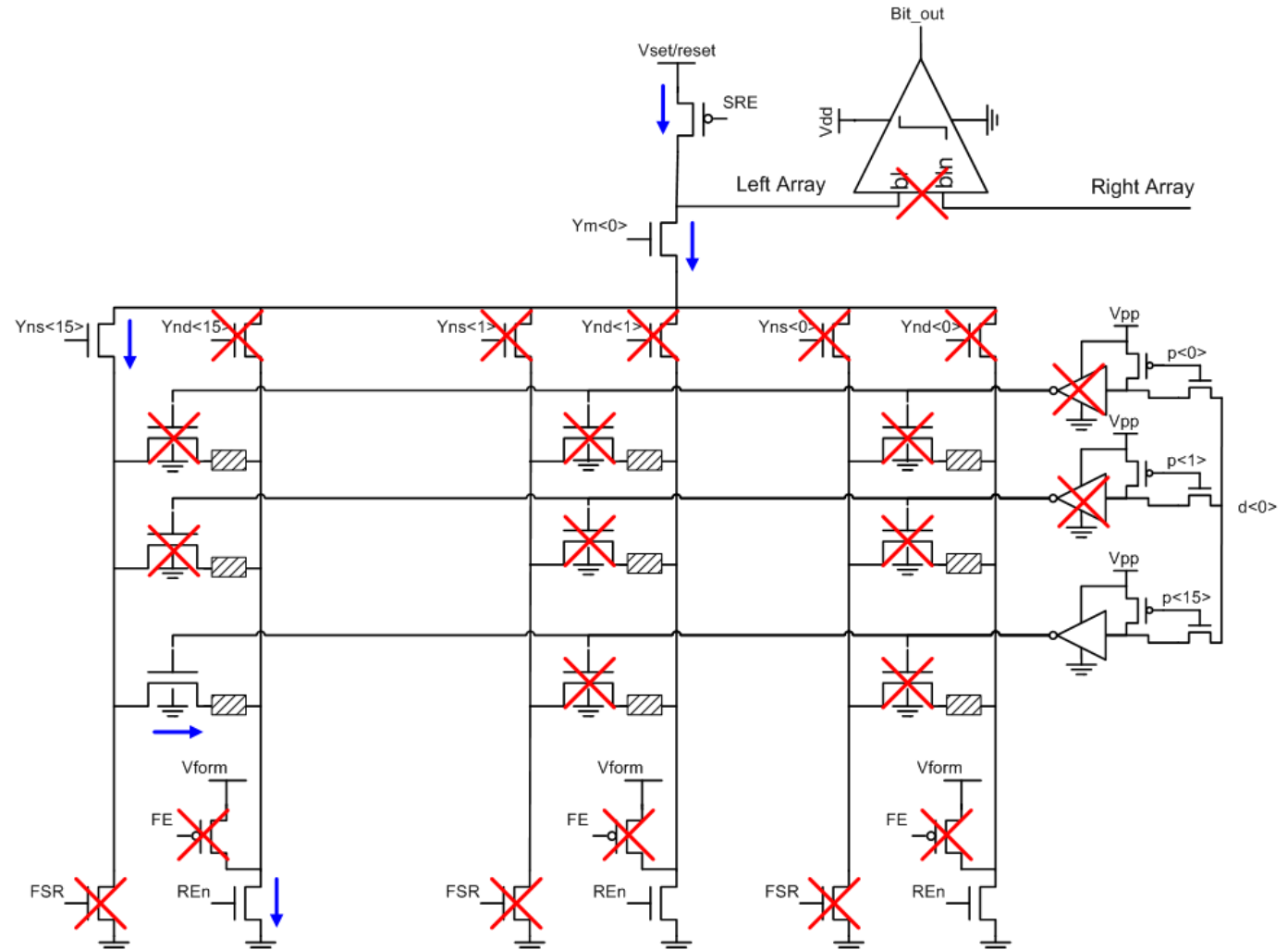



# Reset Mode

$V_{reset} = 2\text{ V}$

$V_{dd} = 2.5\text{ V}$

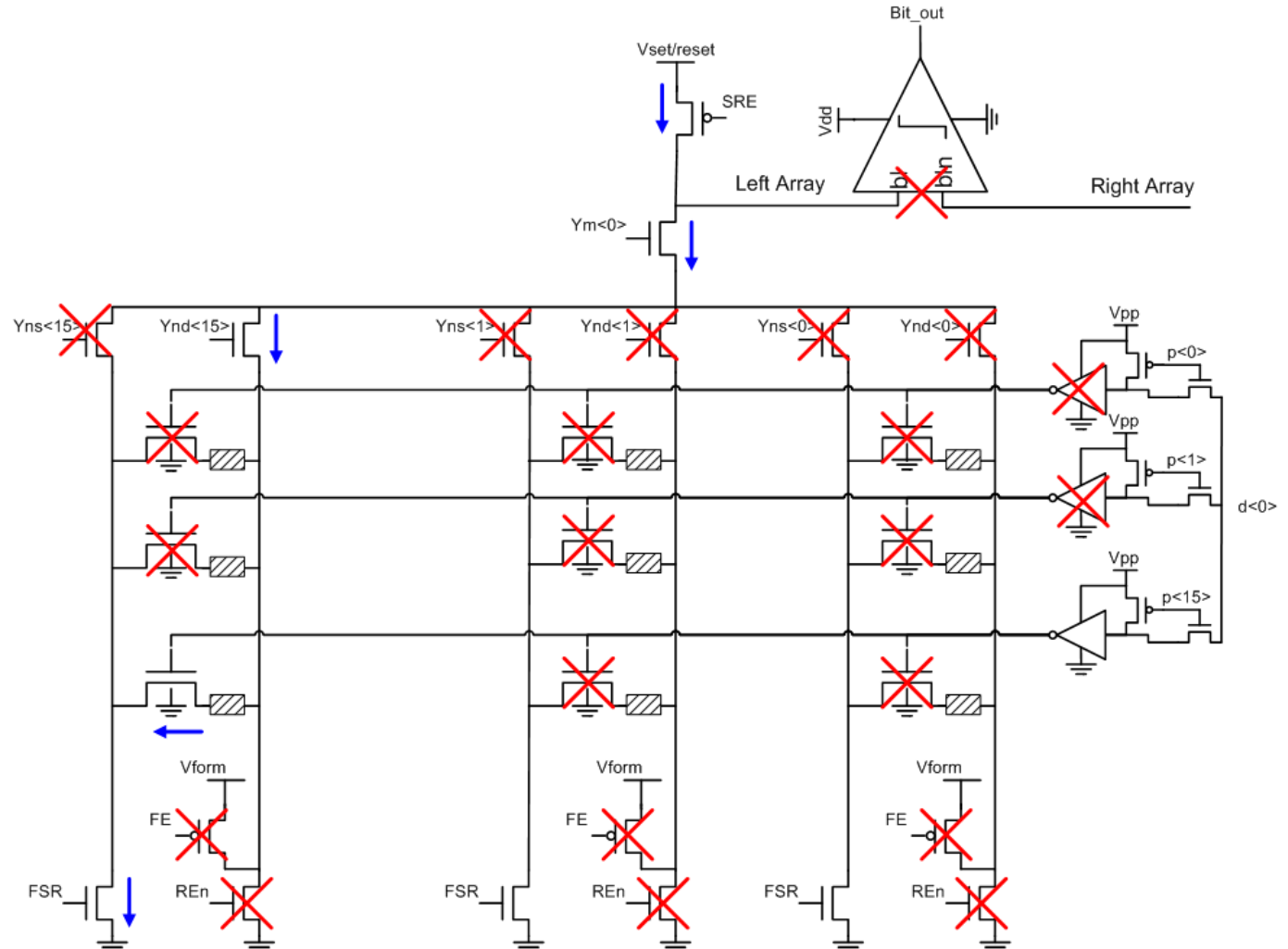
$V_{pp} = 2.4\text{ V}$





# Set Mode

$V_{set} = 2 \text{ V}$   
 $V_{dd} = 2.5 \text{ V}$   
 $V_{pp} = 0.9 \text{ V}$



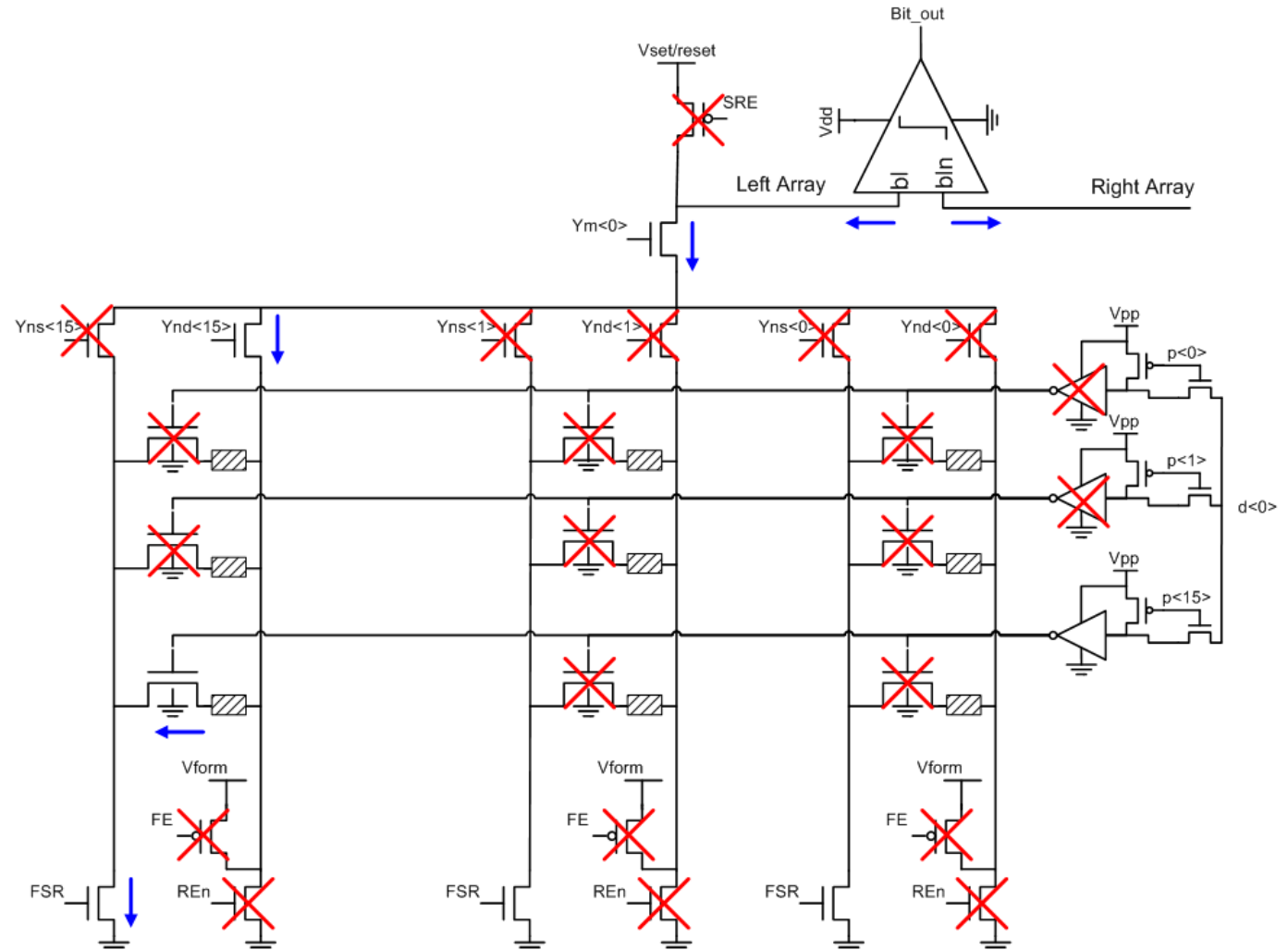



$$V_{pp} = 0.9 \text{ V}$$



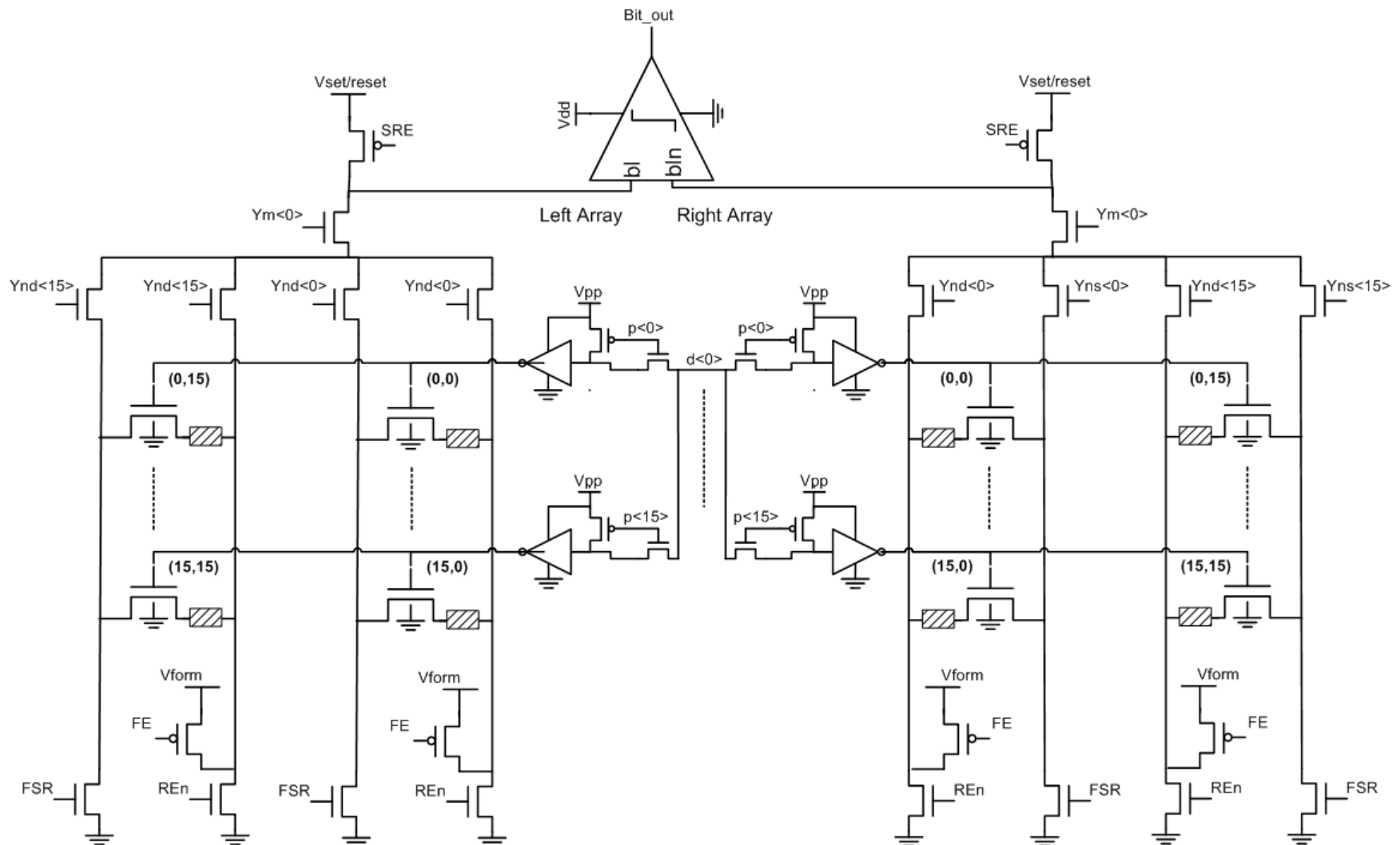

# Read Mode

$V_{set} = 0 \text{ V}$   
 $V_{dd} = 2.5 \text{ V}$   
 $V_{pp} = 0.9 \text{ V}$



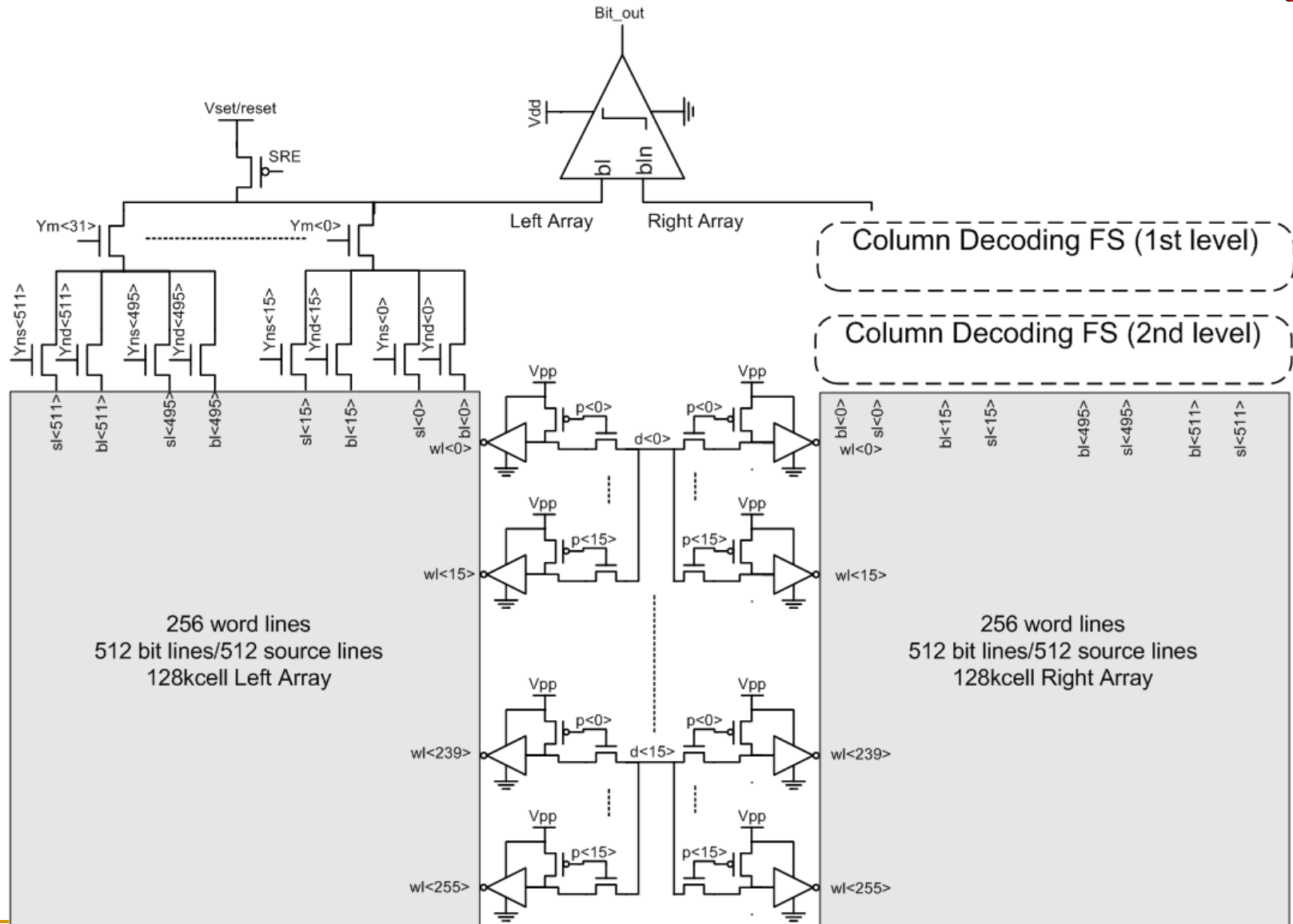
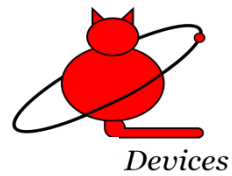


# 16 x 16 Differential Bank





# 128kbit Differential Block



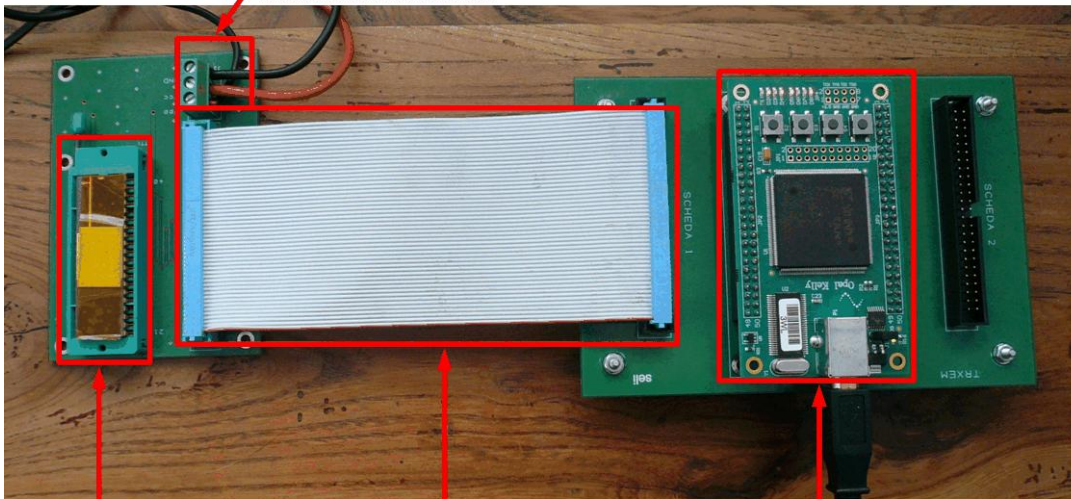


# Testing Equipment

Hardware Based on Xilinx  
Spartan FPGAs



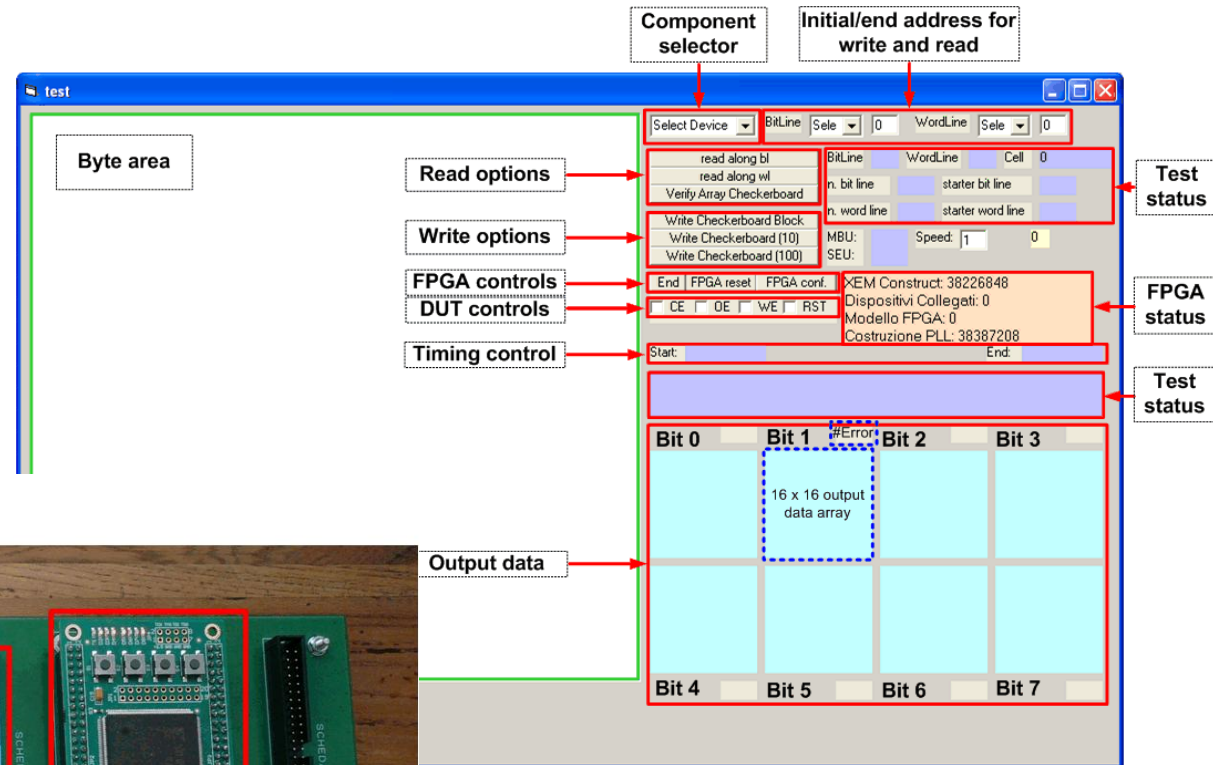
Power connector



DUT

Flat cable connector

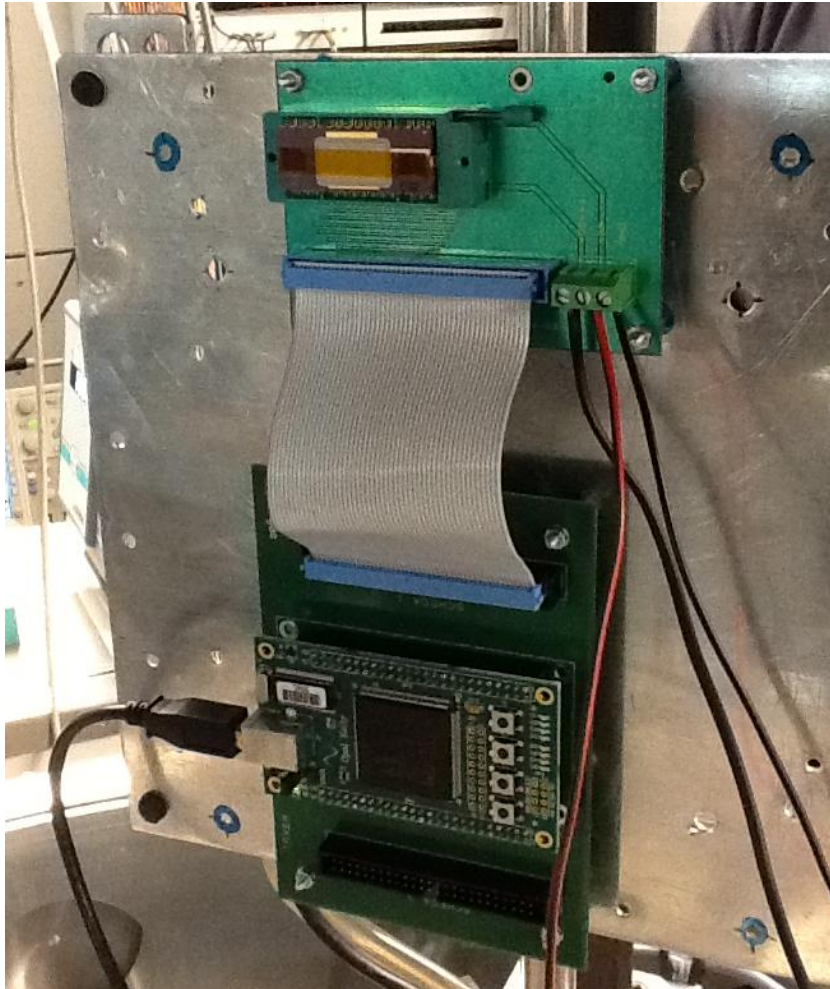
FPGA XEM-3001



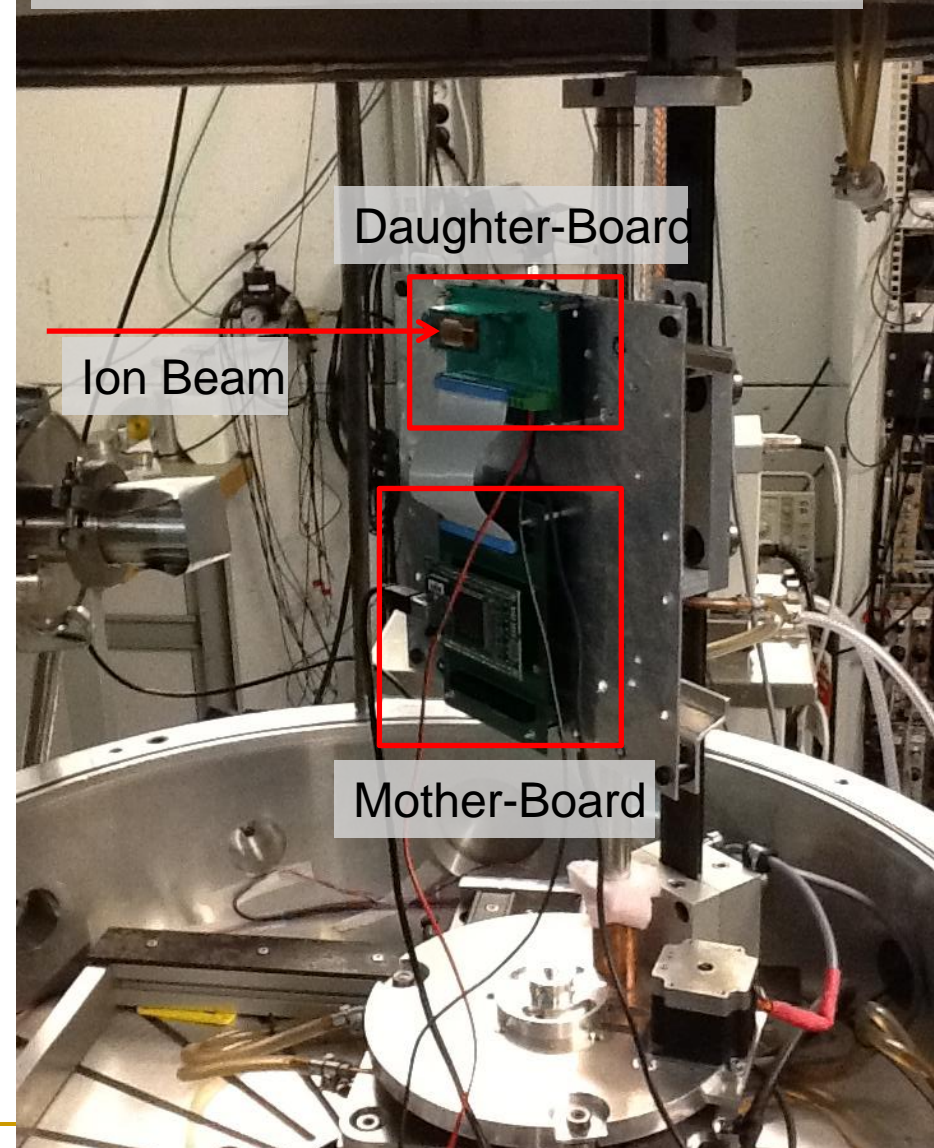
Software Based on Verilog and VB



# Testing Equipment (SEE)

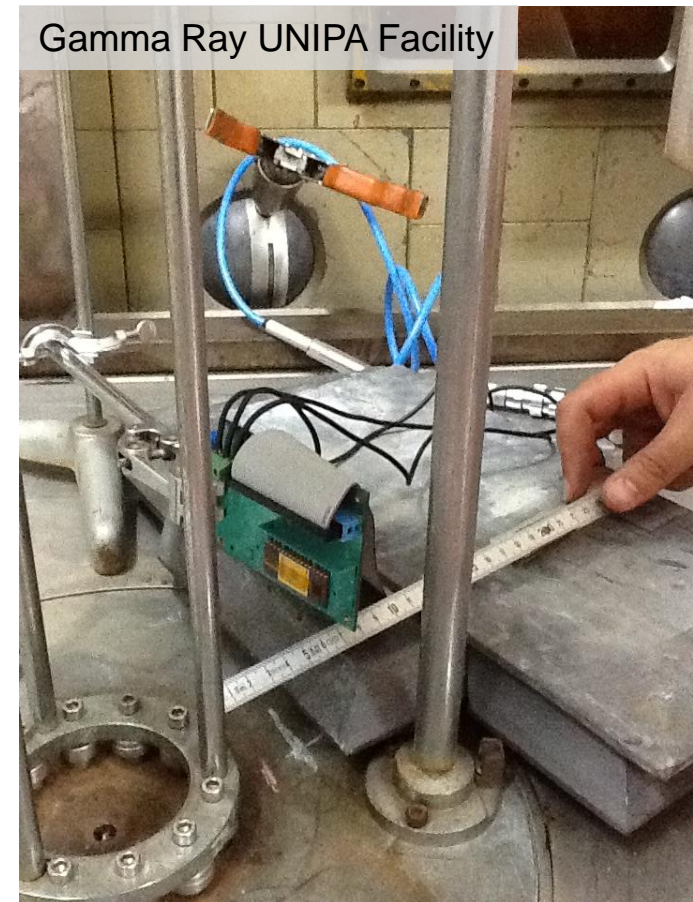
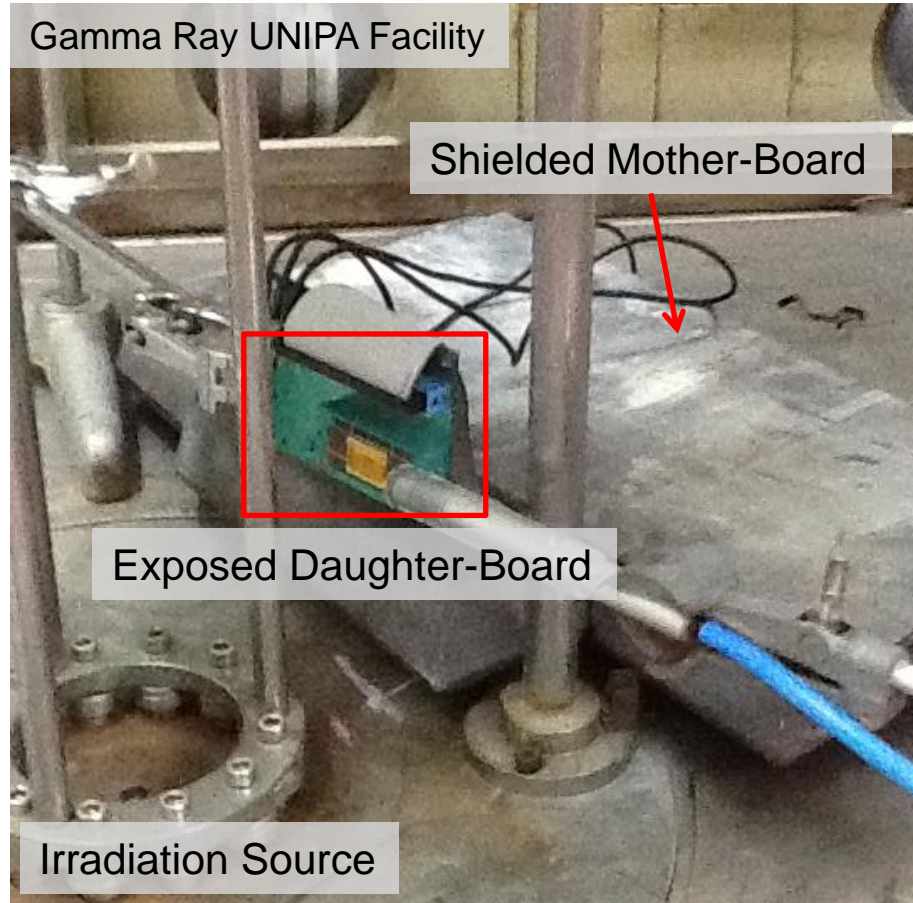


Heavy Ion RADEF Facility (Jyvaskyla, Finland)





# Testing Equipment (TID)





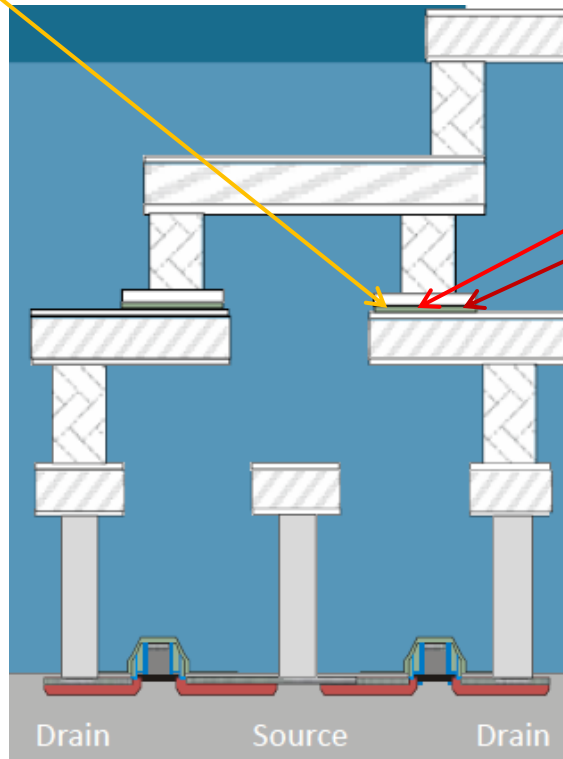
# Some questions looking for an answer

Problem N° 1: Effect of heavy ions on ReRAM!

Problem N° 2: Effect of protons on ReRAM!

Problem N° 3: Effect of gamma on ReRAM!

Gamma Ray



Heavy Ions (Xe, Kr, Si)

Protons

Are filaments broken?  
Do we have nuclear reaction with protons?  
Is there a degradation of ReRAM cells?  
Is Displacement Damage an issue?





# Thanks for your Attention!!

